



SOIPIX
Silicon-On-Insulator Pixel Detector Project

Integration-type SOI pixel sensor

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May 9, 2017
IPHC, Strasbourg, France

Outline

Development history

Developed SOI sensors

- -DIPIX (column ADC study)
- FPIX(1,1b, 2,3)
- INTPIXh2 (radiation tolerance study)
- INTPIX4-8

DAQ system (current and future plan)

Summary & Future prospects

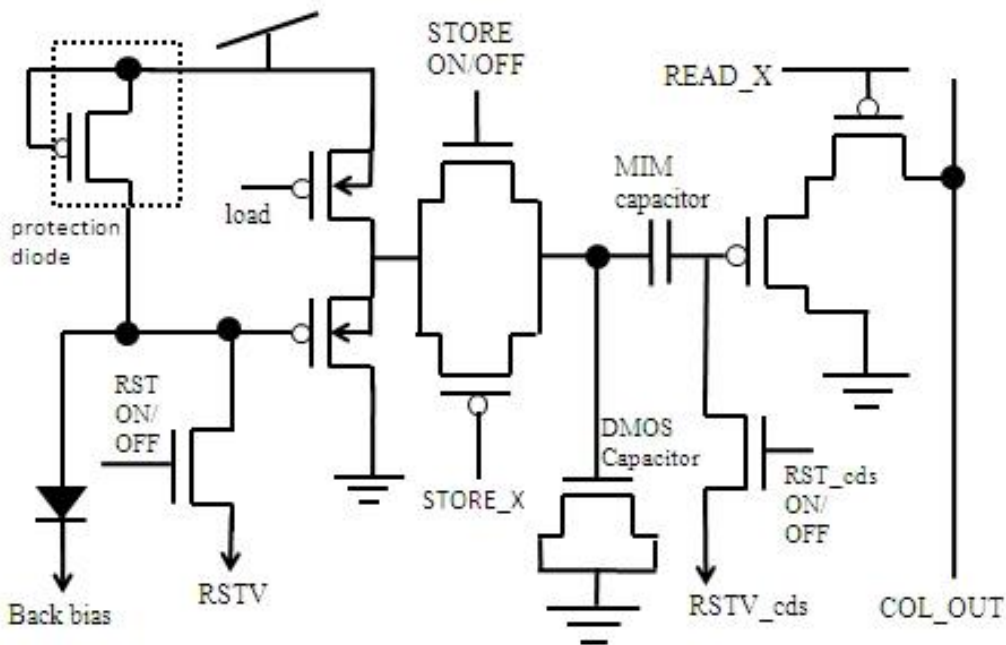
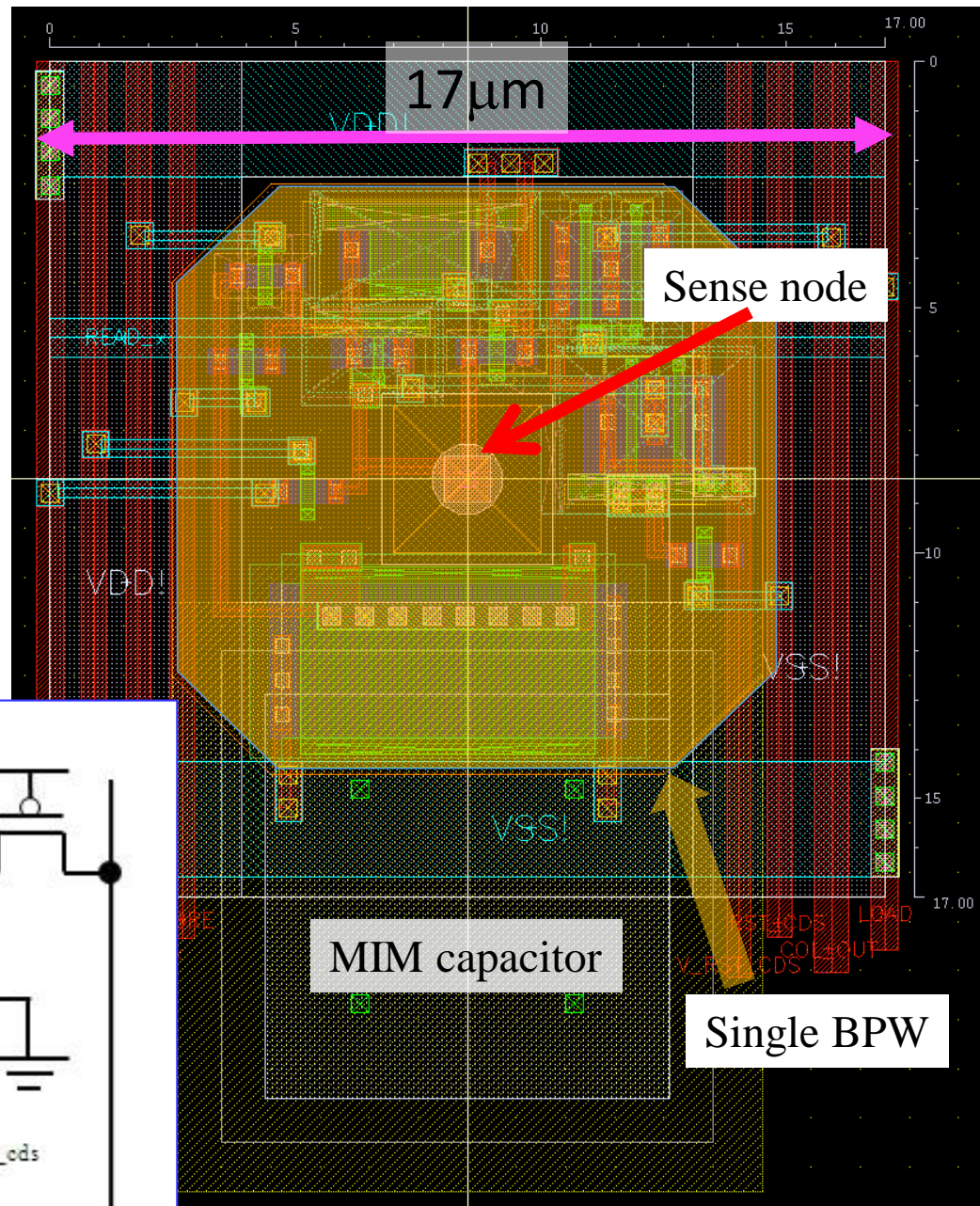
Features of integration-type SOI pixel sensors

Simple pixel circuit

Small pixel size

- w./o. storage capacitor > 8 μ m
- w. storage capacitor > 12 μ m

Good for basic evaluation tests

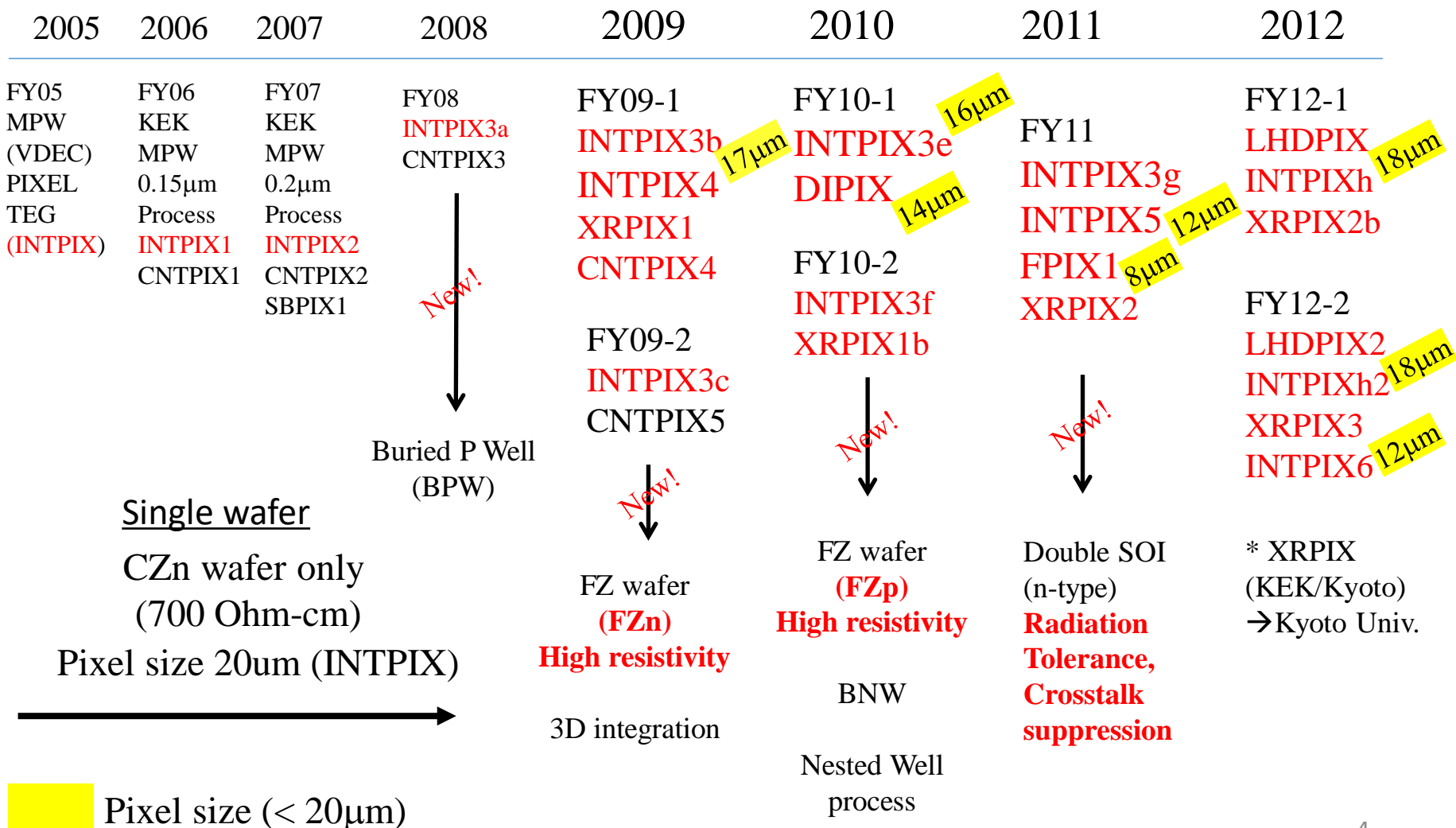


INTPIX4 (2009)

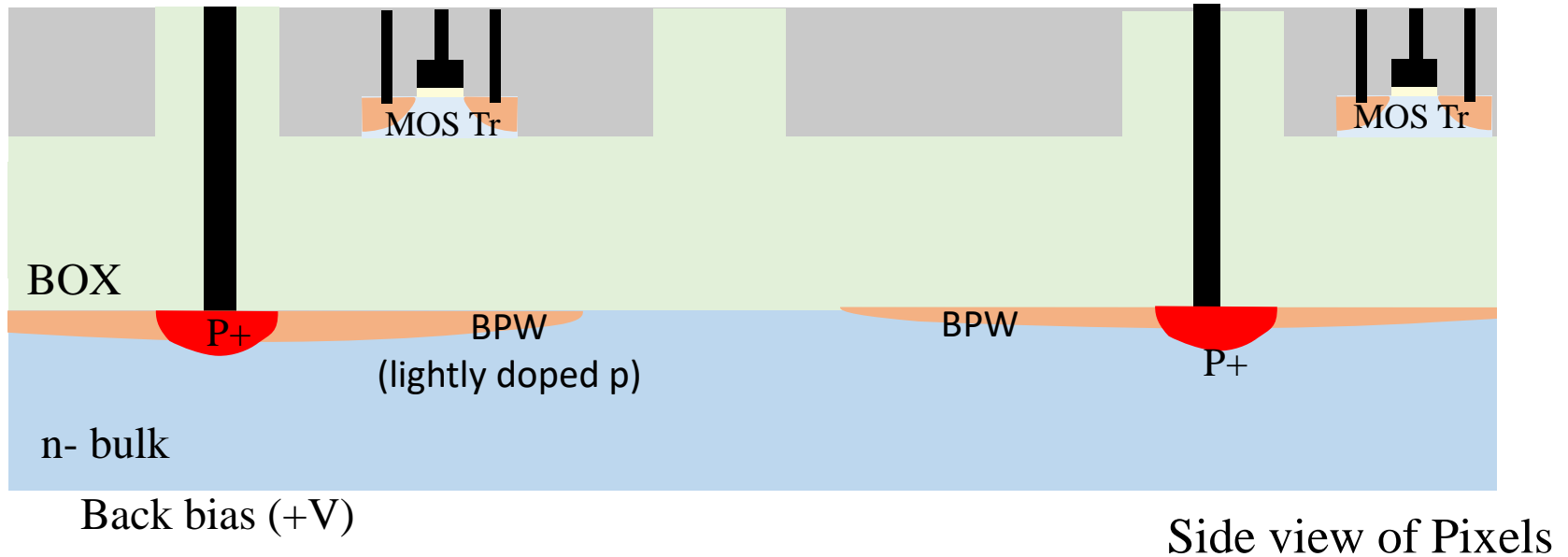
Development history (1)

KEK pixel sensors (red: integration)

Integration-type, counting-type, binary, etc.



Buried-P Well process (2009-)

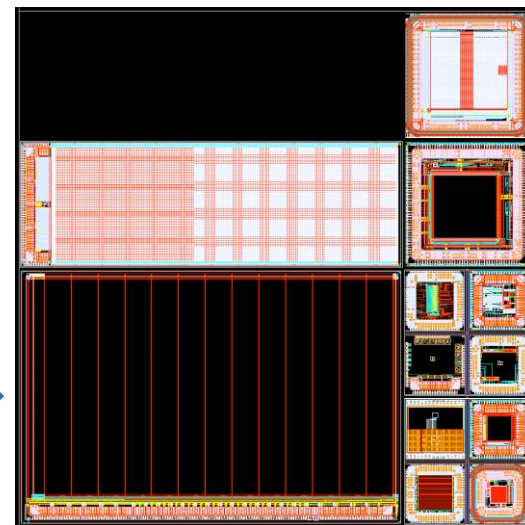
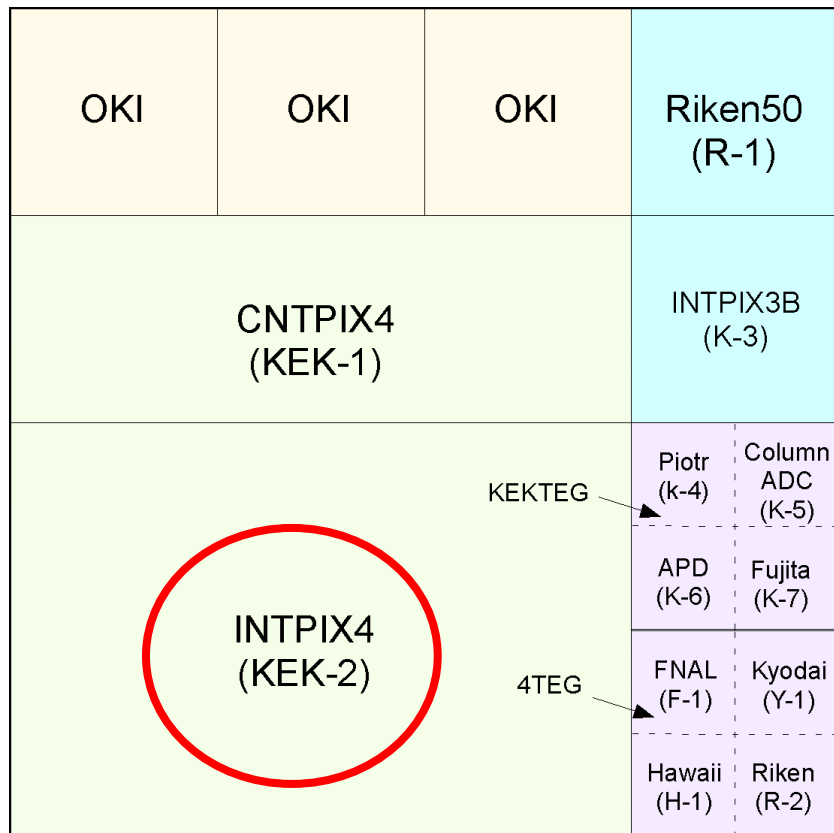


Shield the back gate effect

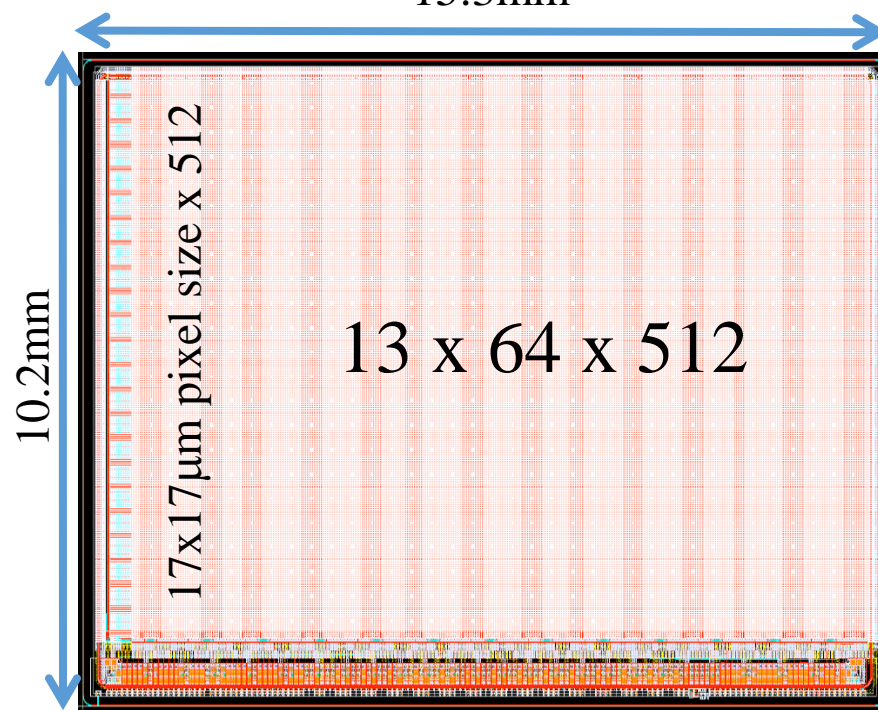
($\sim 2\text{V}$: visible light detection \rightarrow $\sim 100\text{ V}$: X-ray detection)

FY09-1 MPW run (2009)

20.4mm x 20.4mm



15.3mm



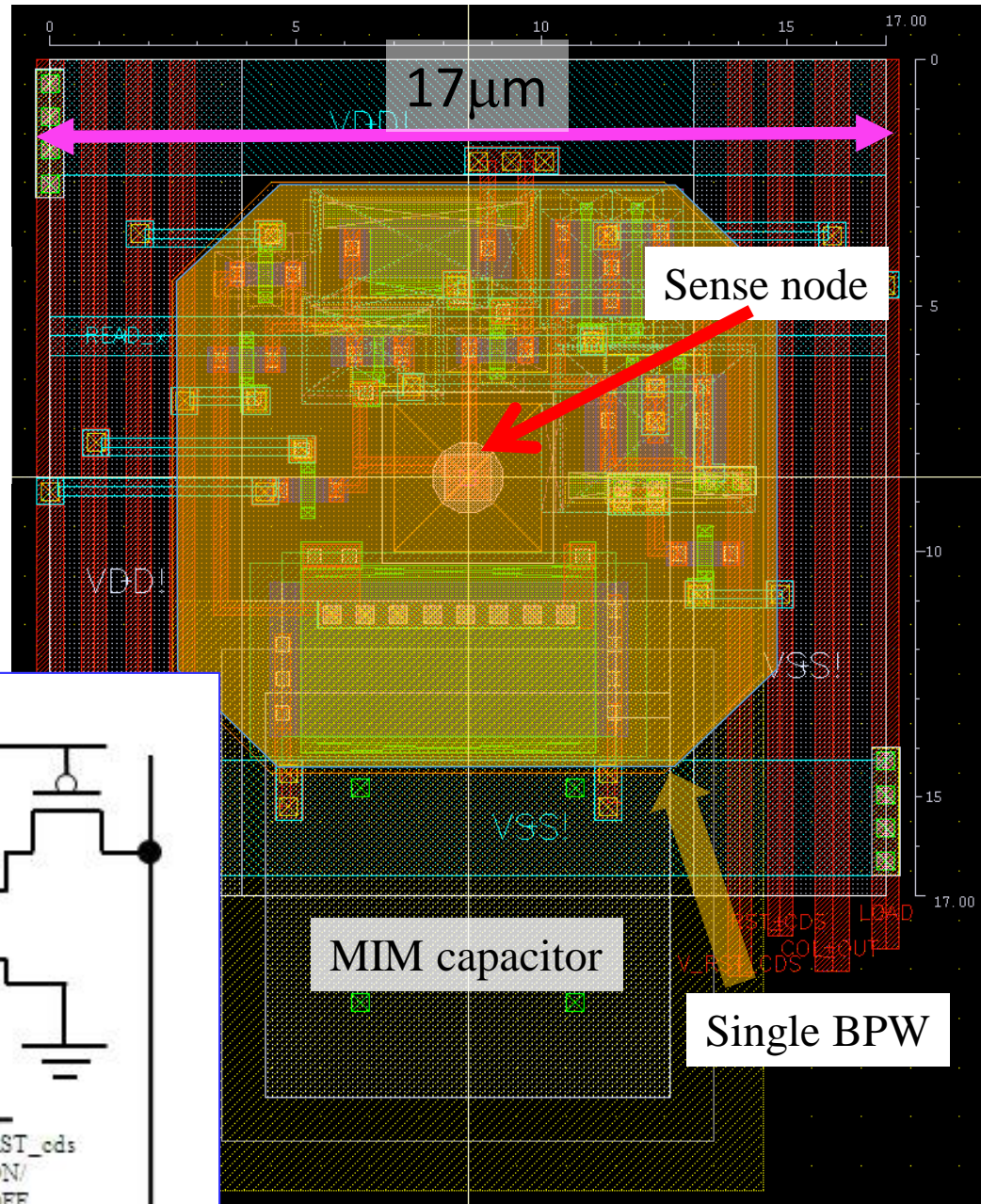
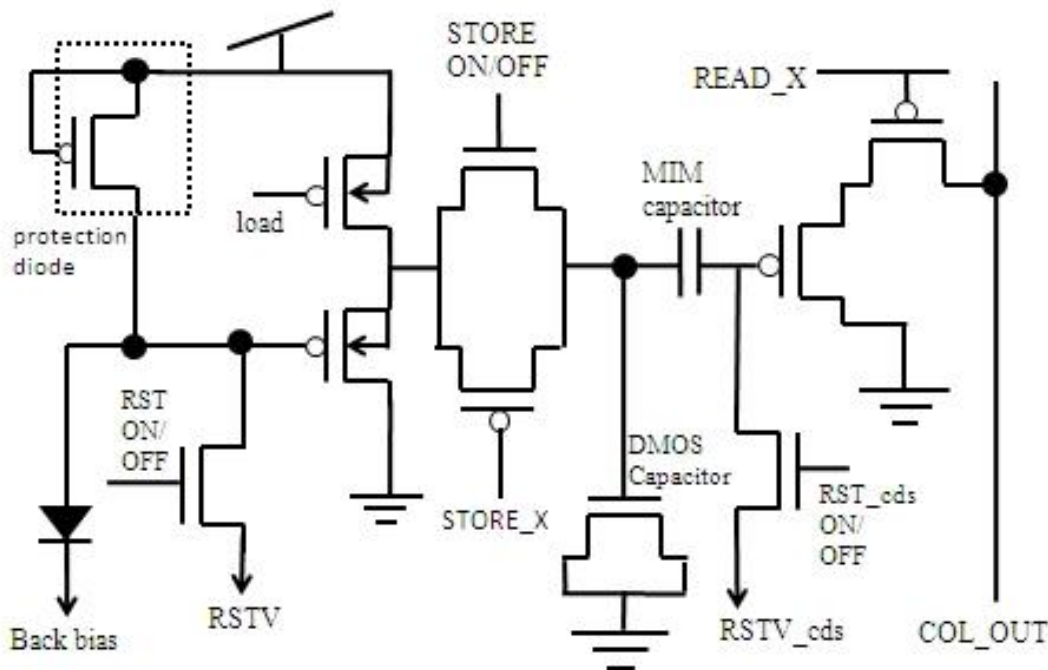
13 analog out

INTPIX4

Pixel Layout

- Pixel size 17 x 17 μm
- Circuit is based on PMOS
- Single BPW inside

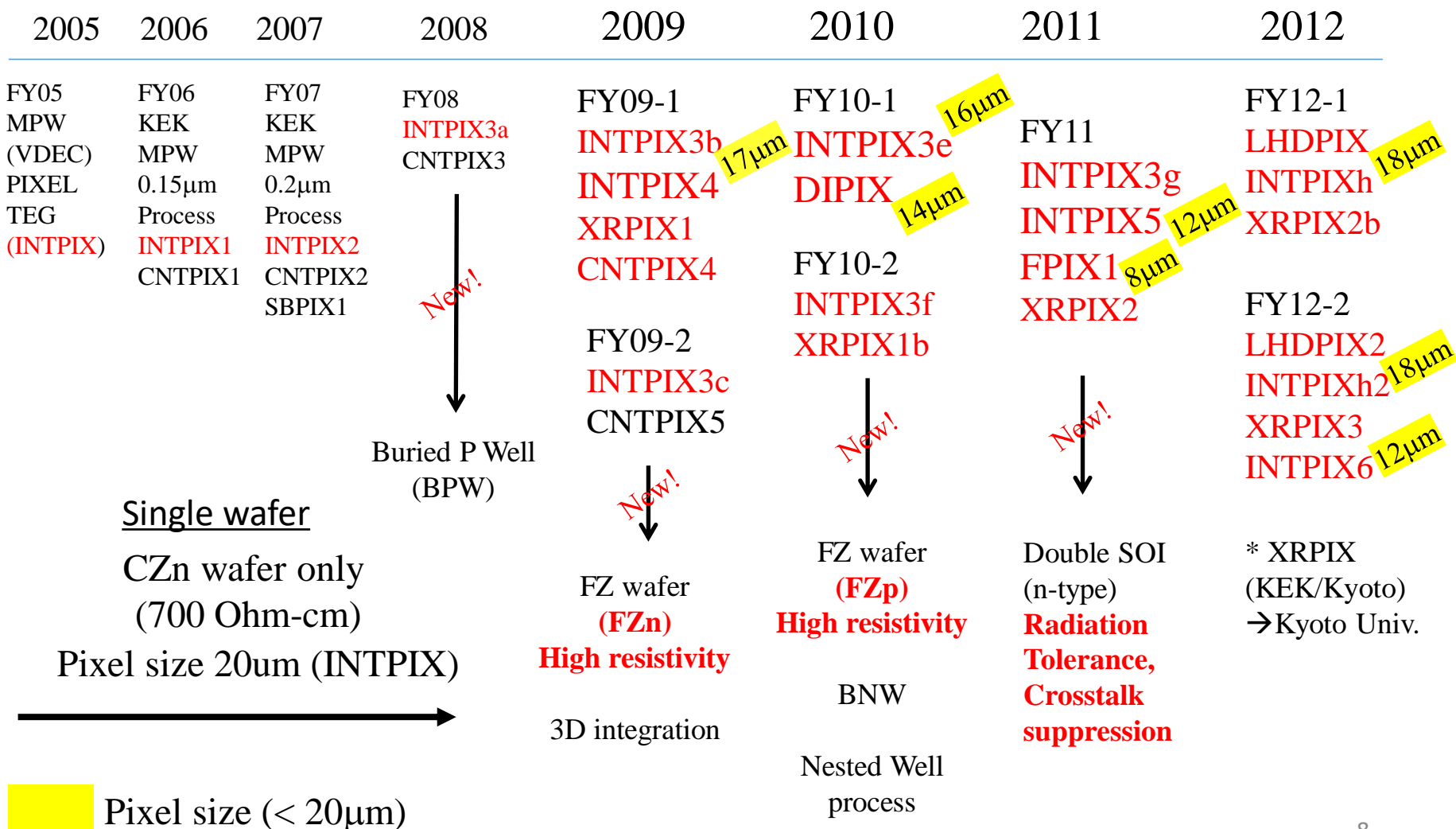
Pixel circuit with CDS



Development history (1)

KEK pixel sensors (red: integration)

Integration-type, counting-type, binary, etc.



Digital output test (DIPIX)

General purpose test chip

Integration-type pixel sensor

P. Kapusta (Krakow)

DIPIX analog output → Column ADC (10bit)

Operational condition

$I_{RG}=0.67\mu A$, $I_{RGSF}=5.2\mu A$, $ADC_CLK=50MHz$

Conversion time 30 us for 50MHz clock

@1.8V limit (core supply),

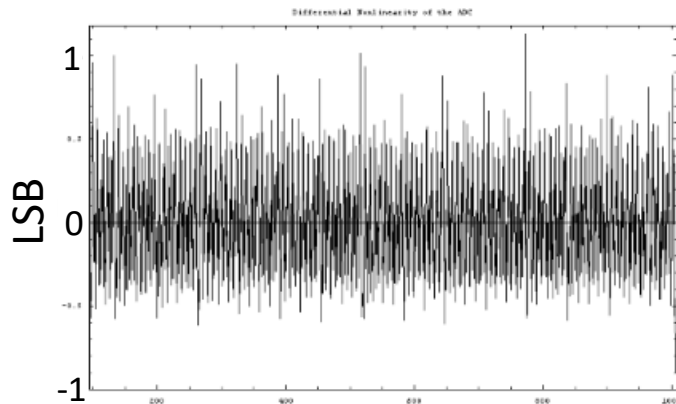
Ramping capacitance 9.9 pF, and

Ramping current 0.67uA

Linearity

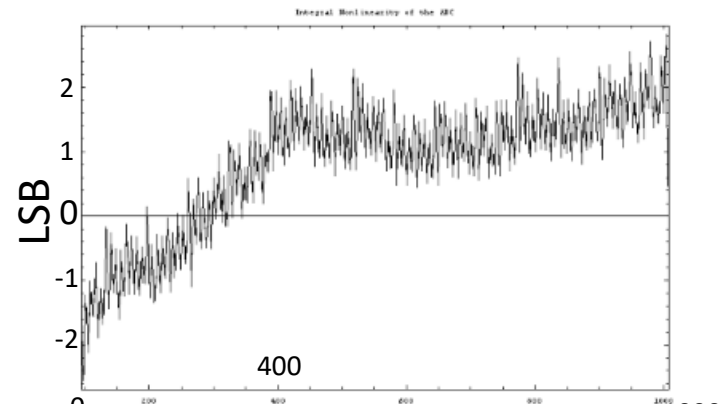
Input signal 720-1780mV (~1V) : ADC 94-1008(10bit).

DNL: -0.95 LSB to 1.13 LSB



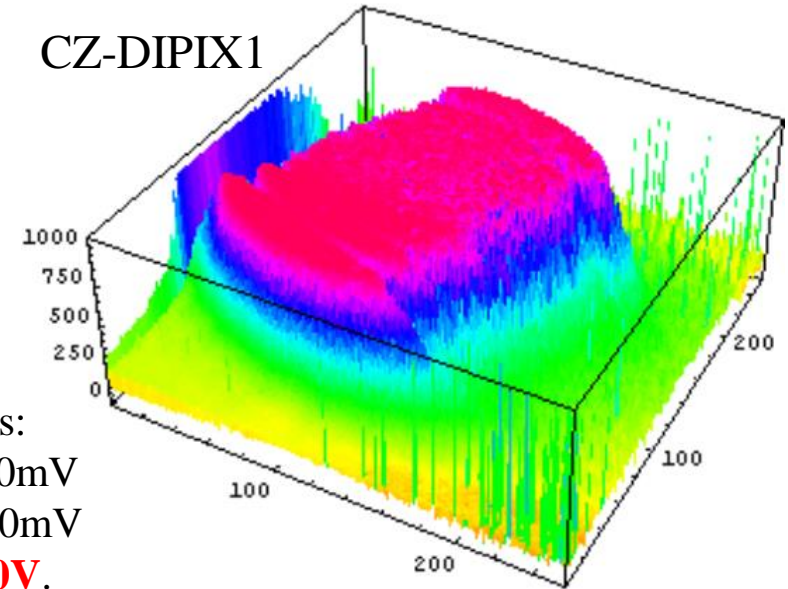
Differential Non Linearity (DNL)

INL: -2.6 LSB to 2.8 LSB



Integral Non Linearity (INL)

CZ-DIPIX1



A red laser image

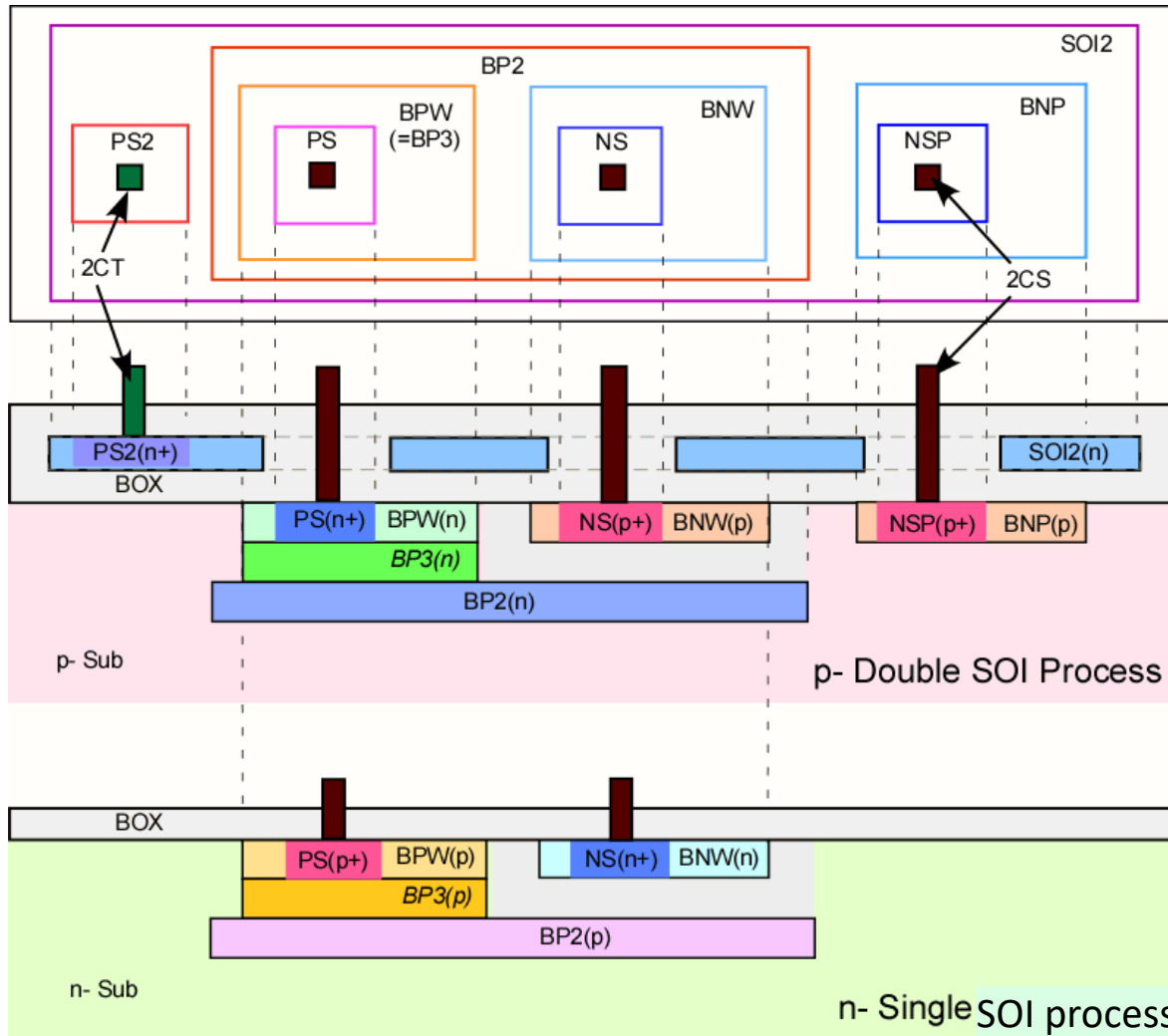
Parameters:

$V_{RSTN}=750mV$

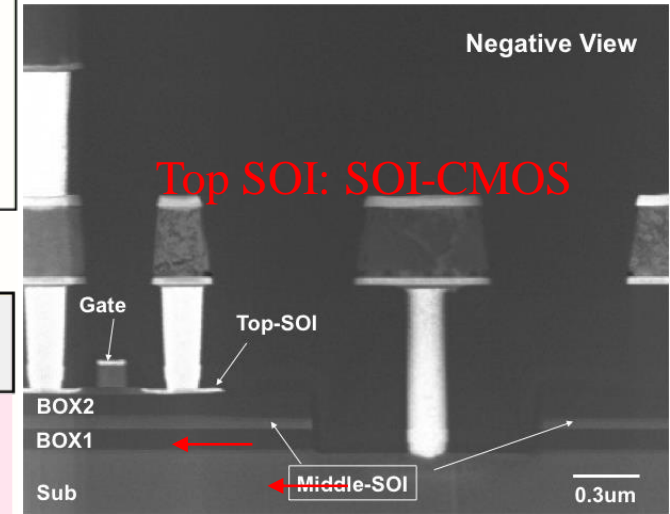
$V_{IPIX}=1800mV$

$V_{DET}=50V$.

Various Implantation Options in Sensor part and Double SOI



Double SOI (DSOI)
STEM image



Middle SOI:
Additional shield layer

p/n various doping density

Shield the back-gate effect / optimize charge collection efficiency

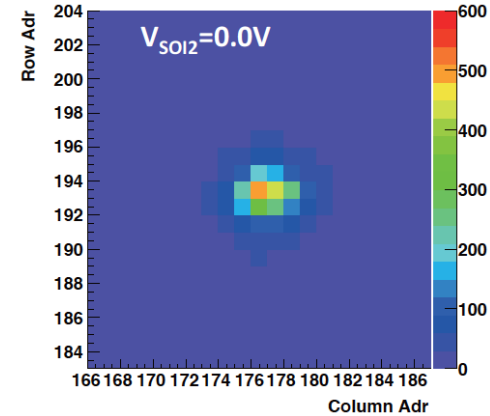
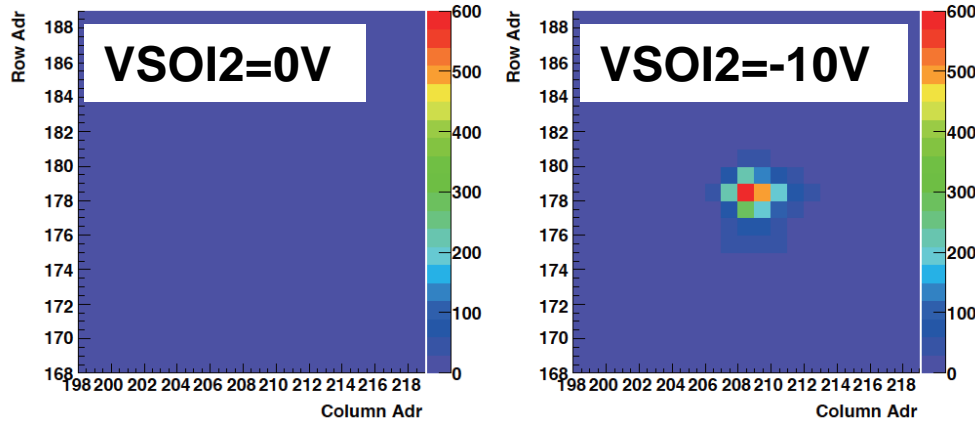
Nested-well process

N-type Double SOI pixel sensor (INTPIXh2)

Sensor test

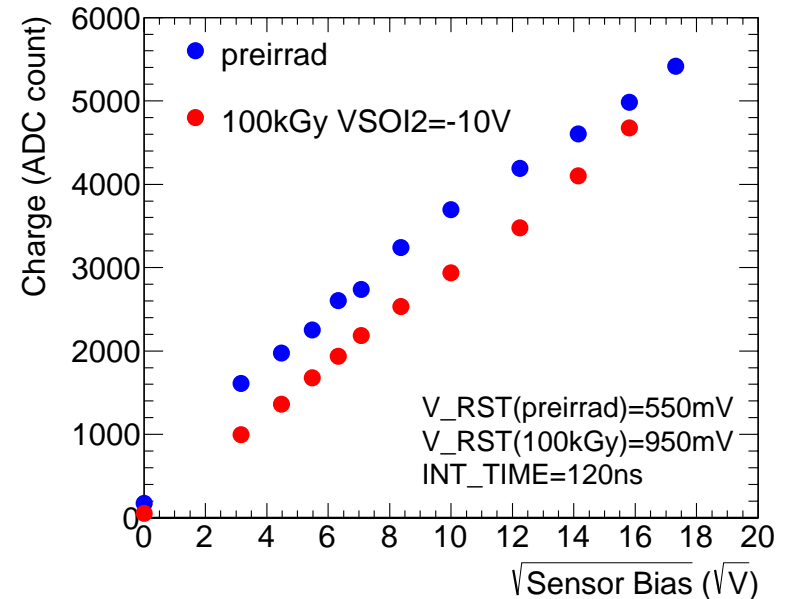
Pre-irrad

Response to infrared laser of 1064 nm wavelength and 10 ns pulse duration.



The pixel images after 100 kGy (10Mrad) could not obtain but recovered with $V_{SOI2}=-10V$.

The average ADC count as function of the square root of the bias voltage for sensor.
→ Obtained similar linearity and sensitivity to pre-irradiation with $V_{SOI2}=-10V$.



S. Honda et al., TIPP2014, 2-6 June 2014, Amsterdam

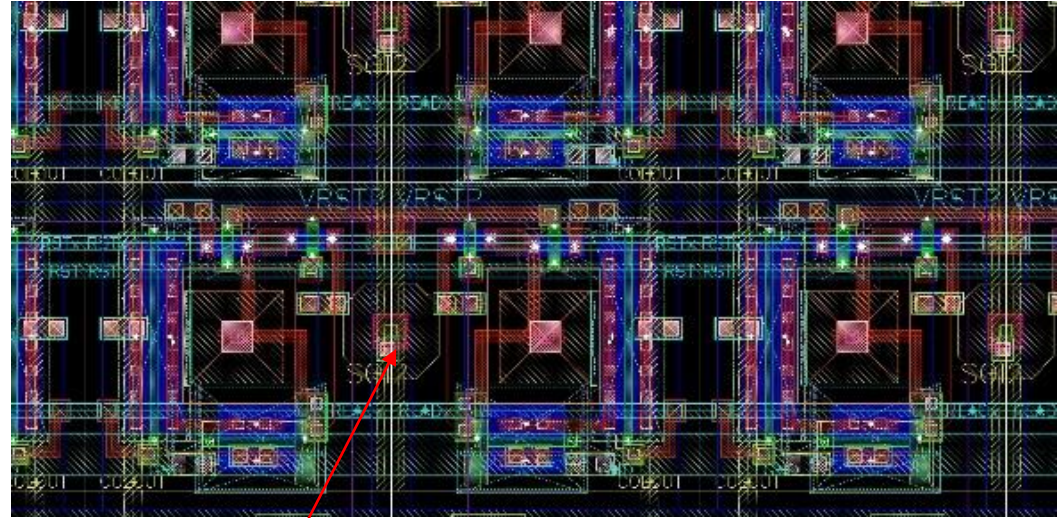
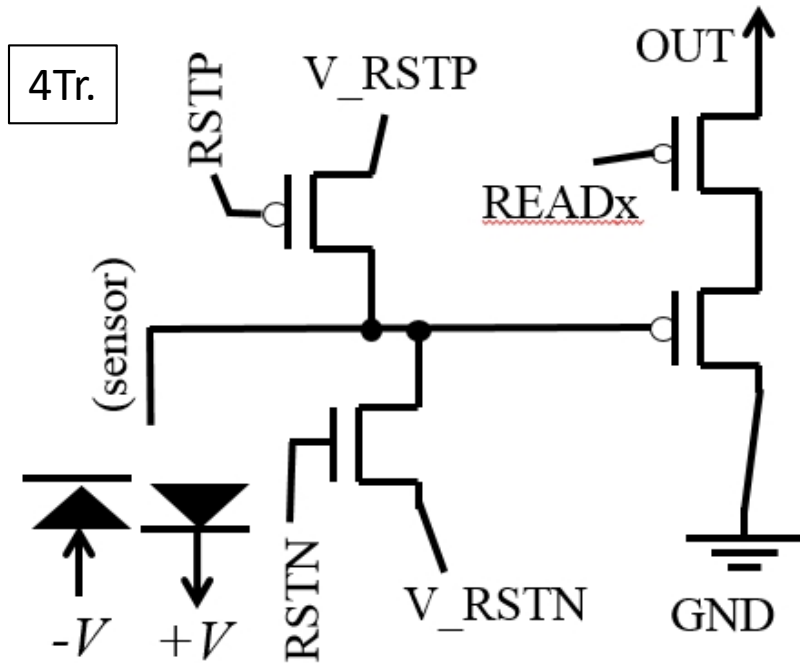
Development history (2)

2012	2013	2014	2015	2016	2017
FY12-1 LHDPIX INTPIXh XRPIX2b	FY13-1 LHDPIX3 INTPIX7 XRPIX3b cpixb	FY14 LHDPIX5 INTPIX8 cpixb3 (MX1786)	M15TEG SOFIST (MX1850)	LHDPIX6 CNPIX1 CPIXPTEG2 SOFIST2 (MX2040)	
FY12-2 LHDPIX2 INTPIXh2 XRPIX3 INTPIX6	FY13-2 LHDPIX4 AXRPIX1 Cpixb2/FPIXb				
	↓ <i>New!</i> Double SOI (p-type) Radiation Tolerance, Crosstalk suppression				
					FPIX1/FPIXb (KEK) FPIX2/3 (Univ. of Tsukuba)

 Pixel size (<20um)

SOI Pixel sensor (8 μm pixel)

fpixb (MX1711): pixel size 8 μm x 512 x 192 pixels



$8\mu\text{m}$
PS2 contact for middle SOI between pixels

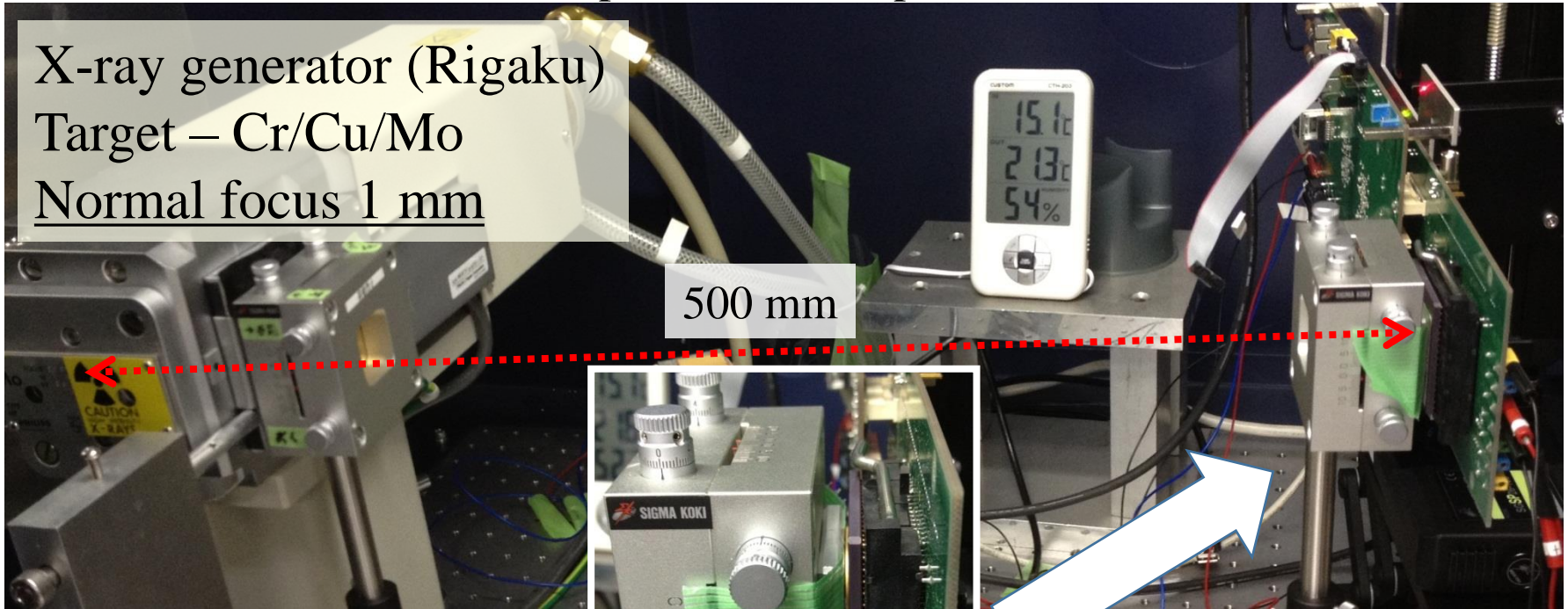
No storage capacitor

Not good at synchronous measurement

Good at asynchronous measurement

Spatial resolution study

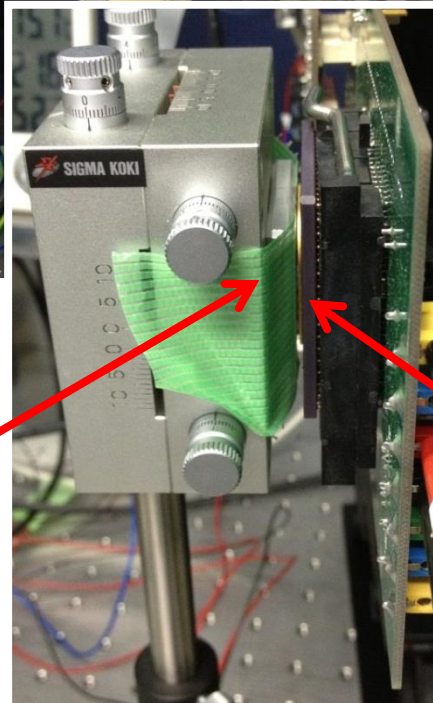
Experimental Setup



X-ray generator (Rigaku)
Target – Cr/Cu/Mo
Normal focus 1 mm

500 mm

- Test chart (Kyokko)
Pb 30 μm
< 20 LP/mm
- Micro chart (JIMA)
Au 1 μm
3-50 μm slits
- X-ray Imaging demonstration



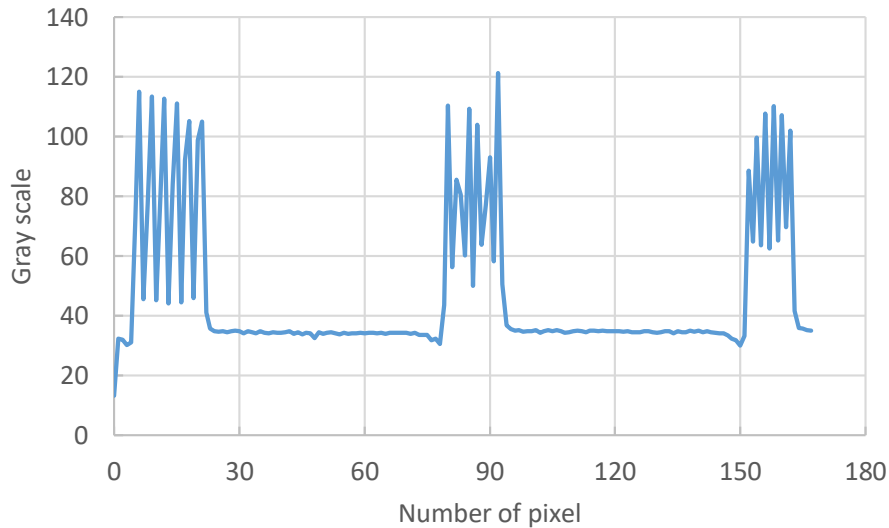
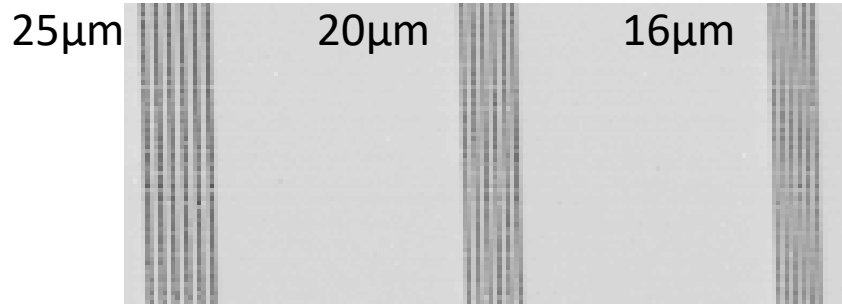
SOI sensors

Spatial resolution

X-ray test chart + X-ray tube

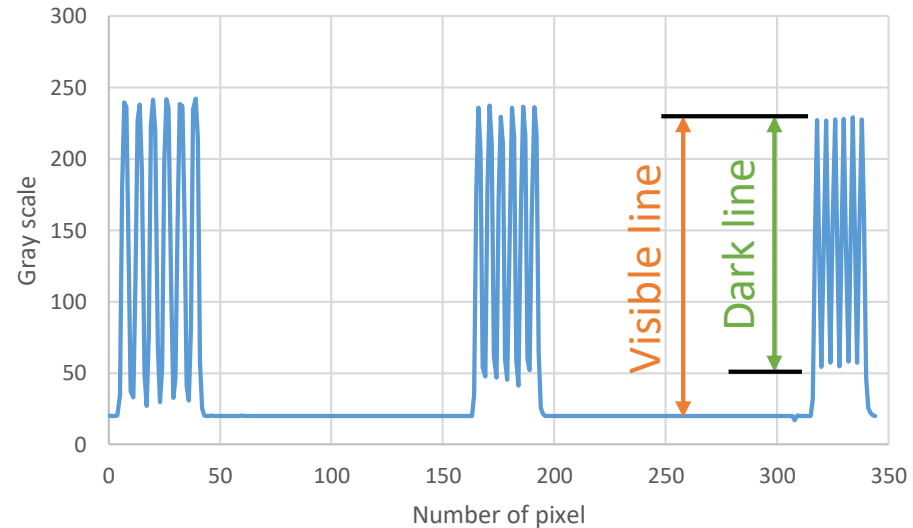
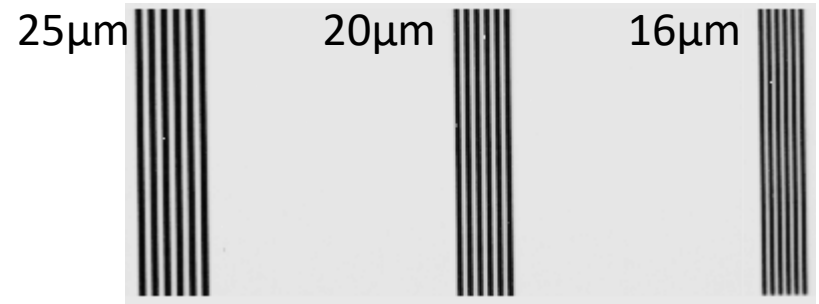
2009

NFZ-INTPIX4 17 μ m pixel



2014

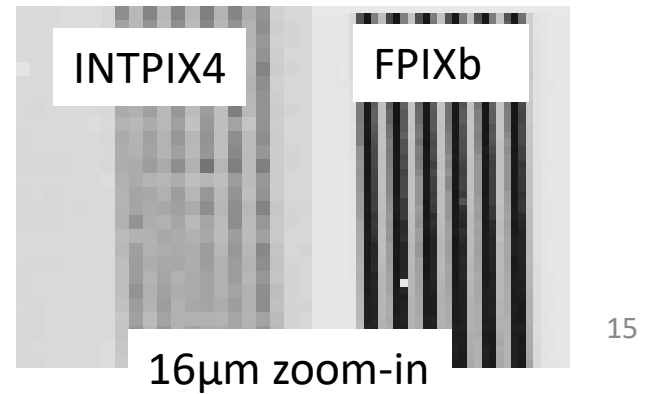
NFZ-FPIXb 8 μ m pixel



- Cu 8keV、20kV、2mA、front illumination, bias 100V

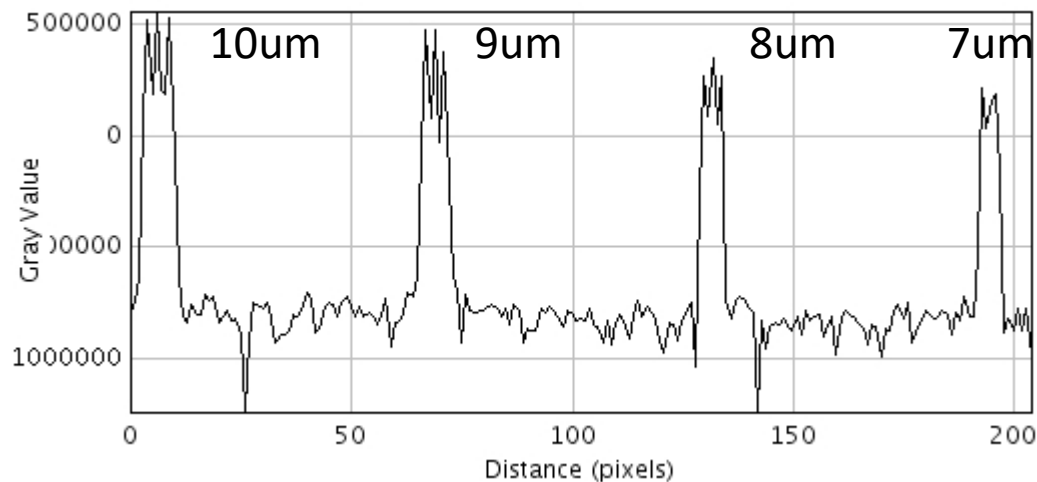
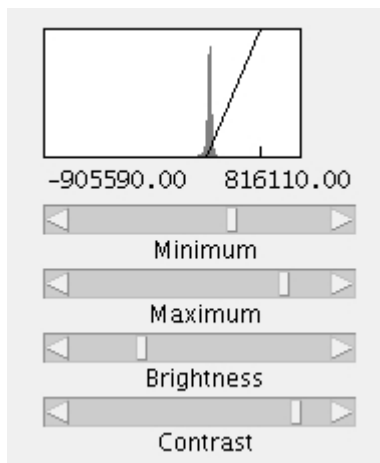
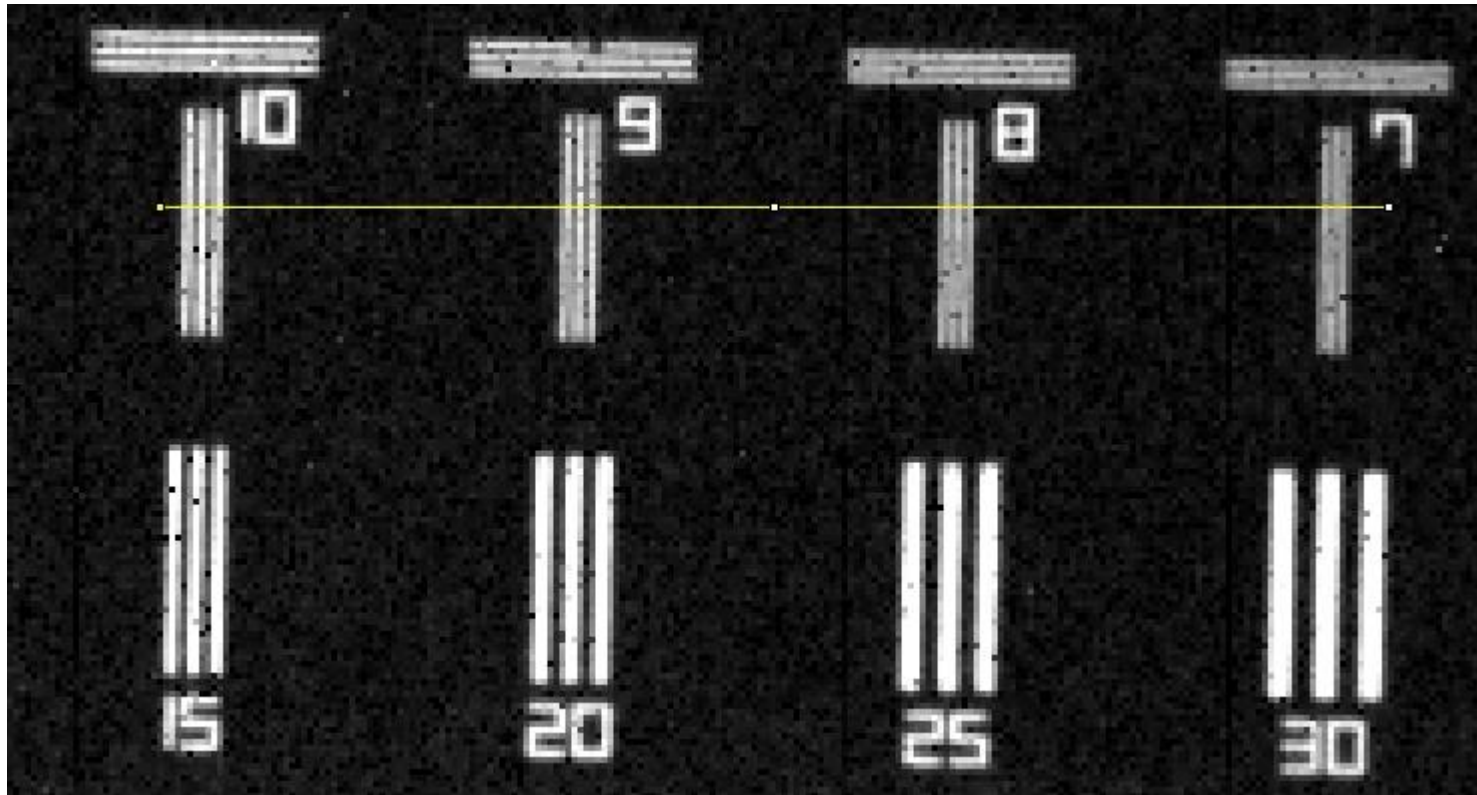
- Ratio 16 μ m slit: Dark line / visible line

INTPIX4(17 μ m) : 0.57、FPIXb(8 μ m) : 0.83



JIMA X-ray test chart image

2015/8/13



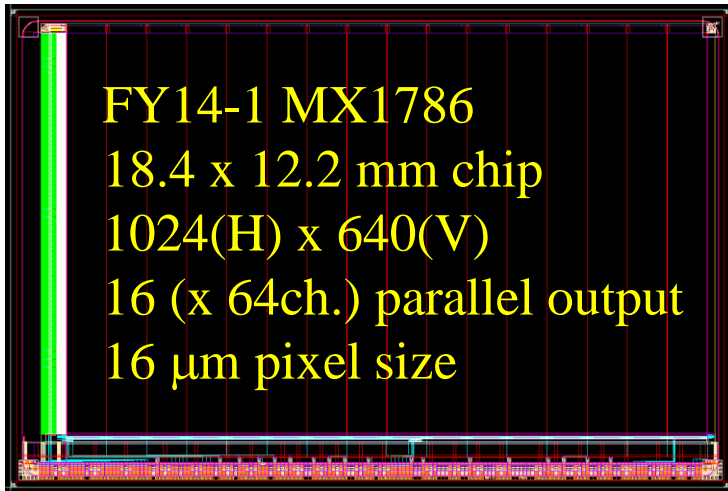
1d histogram

8um --- 3 slits

INTPIX4-8

	INTPIX4	INTPIX5	INTPIX6	INTPIX7	INTPIX8
Process	MX1350	MX1501	MX1594	MX1655	MX1786
Pixel size	17 um sq	12 um sq	12 um sq	12 um sq	16 um sq
# of pix.	512 x 832 (425, 984 pix)	896 x 1408 (1, 261, 568)	896 x 1408 (1, 261, 568)	1408 x 1408 (1, 982, 464)	640 x 1024 (655, 360)
Chip size	10.2 x 15.4mm ²	12.2 x 18.4 mm ²	12.2 x 18.4 mm ²	18.4 x 18.4 mm ²	12.2 x 18.4 mm ²
Sensitive area	8.7 x 14.1mm ²	10.7 x 16.9 mm ²	10.7 x 16.9 mm ²	16.9 x 16.9 mm ²	10.9 x 17.4
Global Shutter	yes	yes	yes	yes	yes
Rolling Shutter	no	yes	yes	yes	yes
Frontend Amp	PMOS Source Follower	PMOS Source Follower	PMOS Source Follower	PMOS Source Follower	PMOS Charge Amp
CDS	In Pixel CDS	Column CDS	Column CDS	In Pixel CDS	In Pixel CDS
Sensor gain	~14uV/e ⁻	~2.5/15 uV/e ⁻	~2.5/15 uV/e ⁻	~16 uV/e ⁻	~12/18/36/80 uV/e ⁻
Gain Sw	no	yes(1bit)	yes(1bit)	no	yes(2bit)
# of output	1or13	1or11	1or11	1or11	1or16
Wafer type	n-type	n-type	INTPIX6n(n, n-DSOI) INTPIX6p(p)	N, p, p-DSOI	N, p, p-dsoi

Integration-type sensor - INTPIX8 (FY14-1)

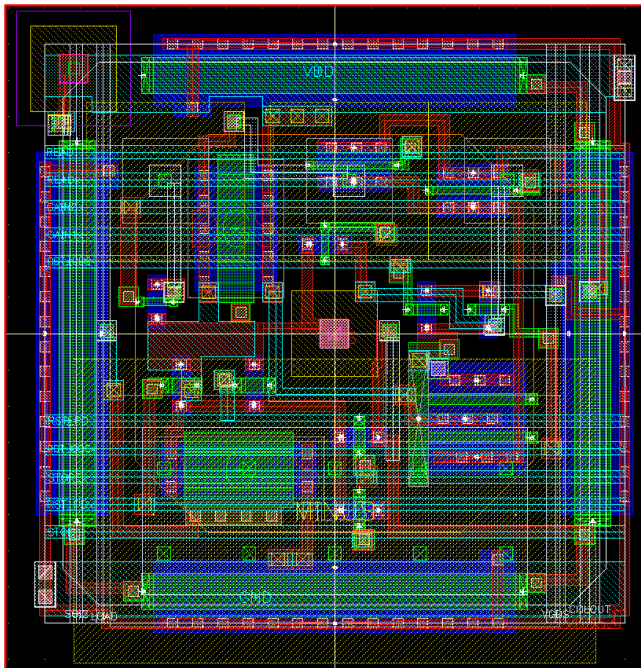


Double SOI (Cz-p) 300 μm

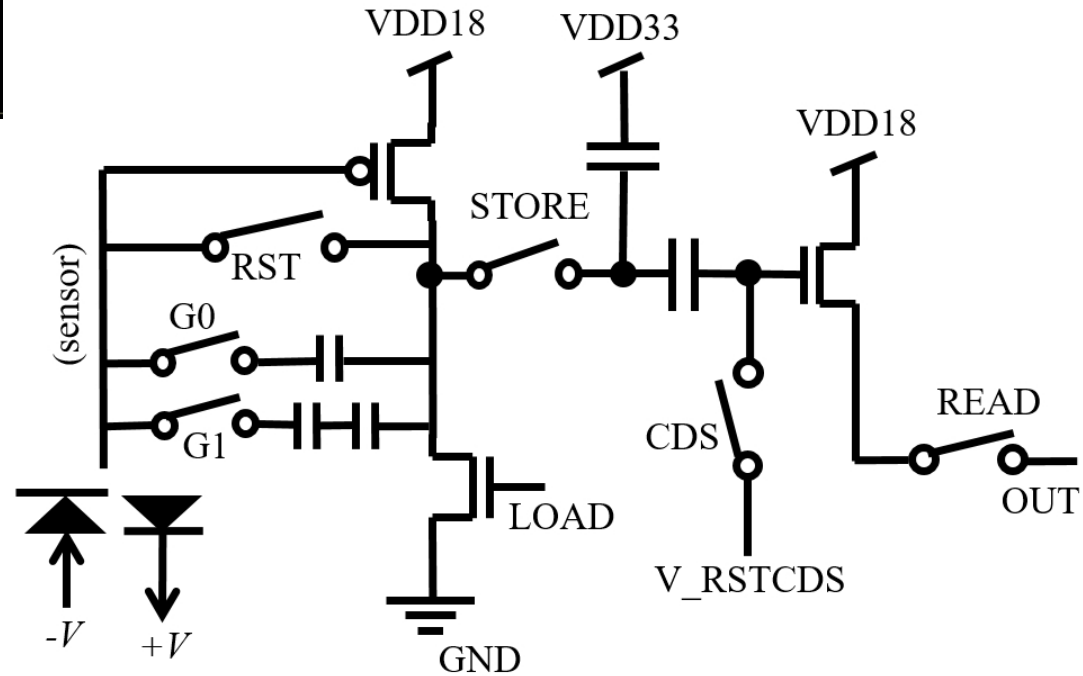
Single SOI (FZ-p) 500 μm

Low gain mode G0,G1 off

High gain mode G0,G1 on

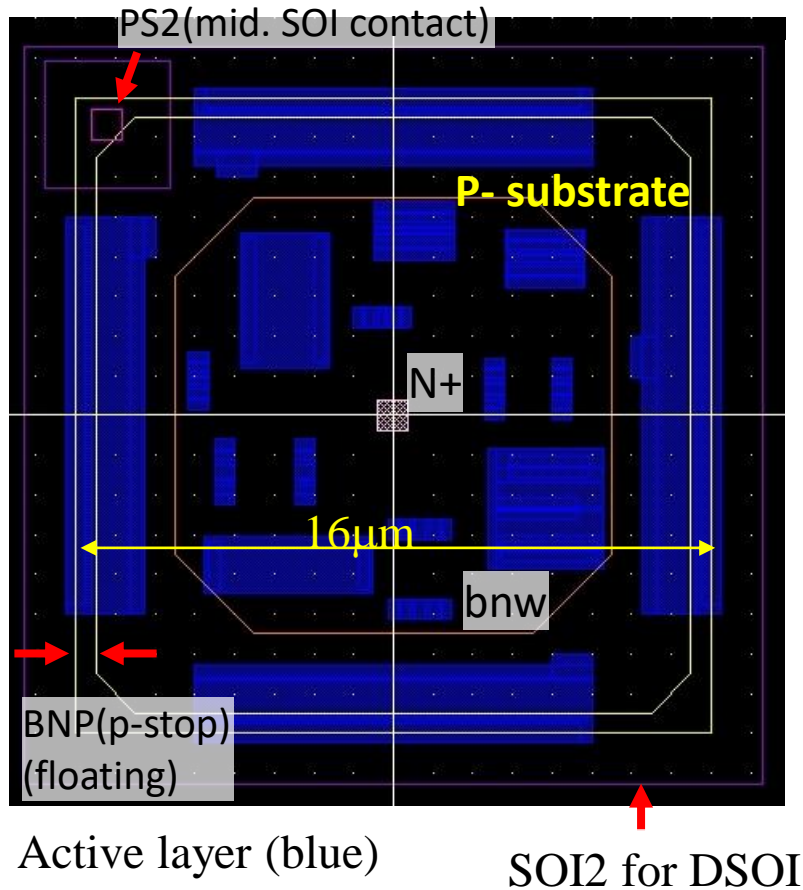


Pixel layout 16 μm x 16 μm

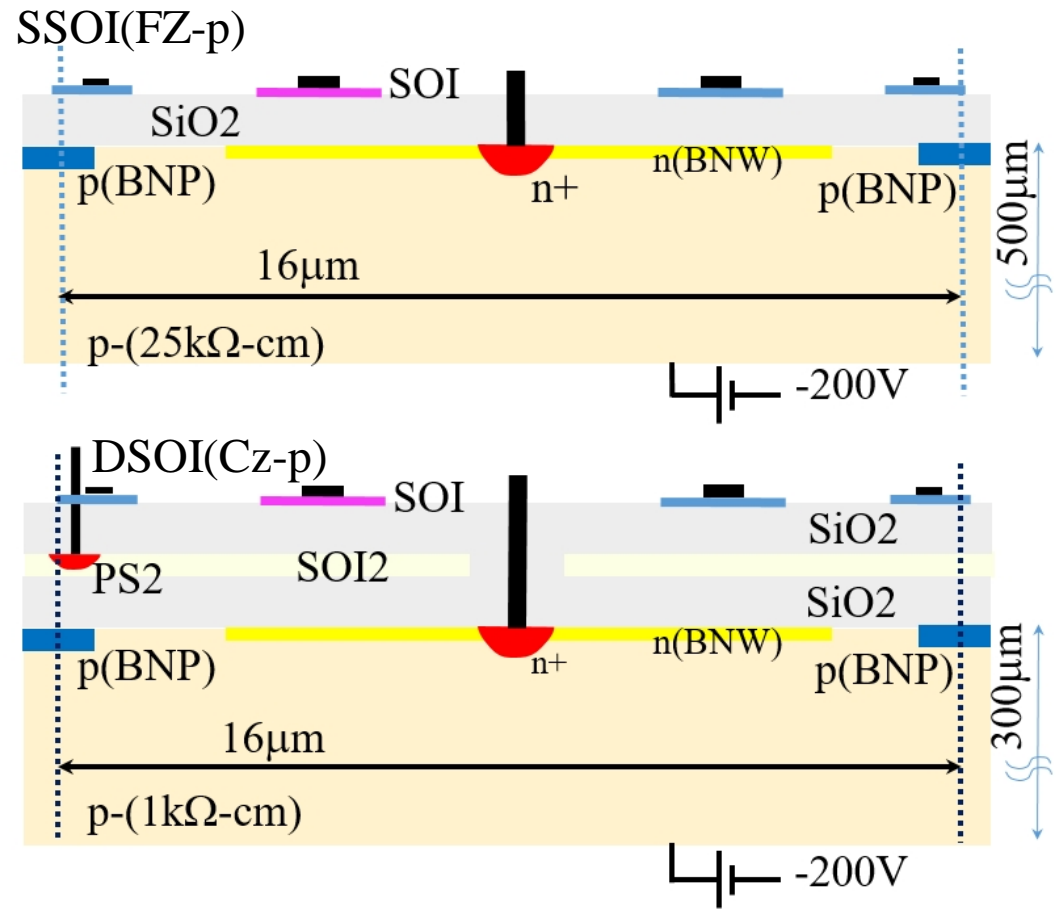


Pixel circuit

Integration-type p-type SSOI/DSOI sensor - INTPIX8 (FY14-1)

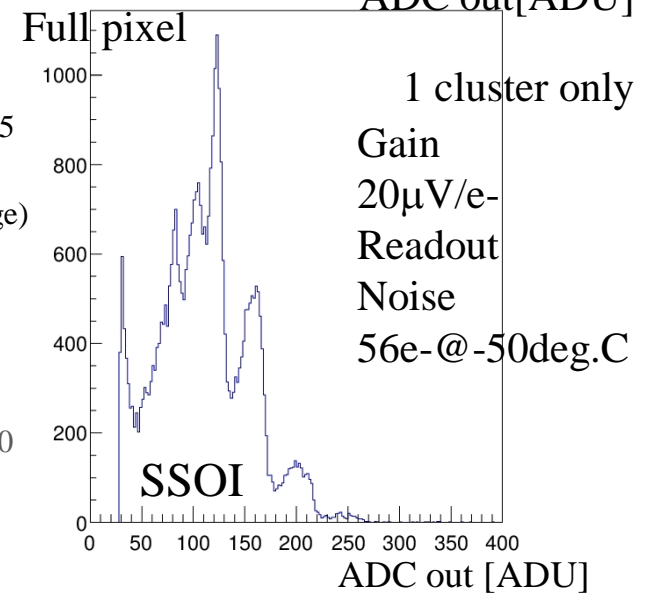
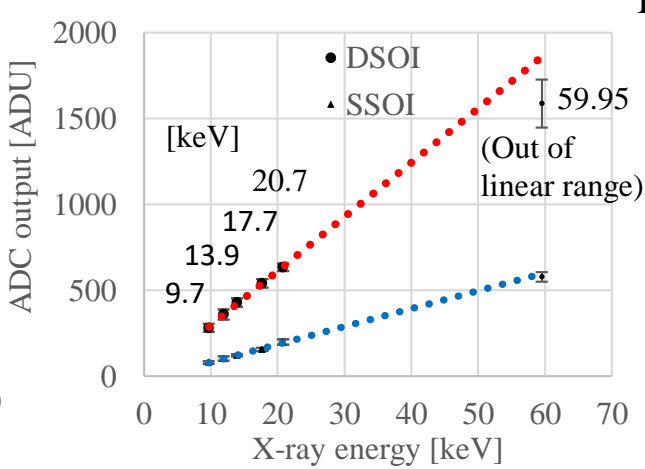
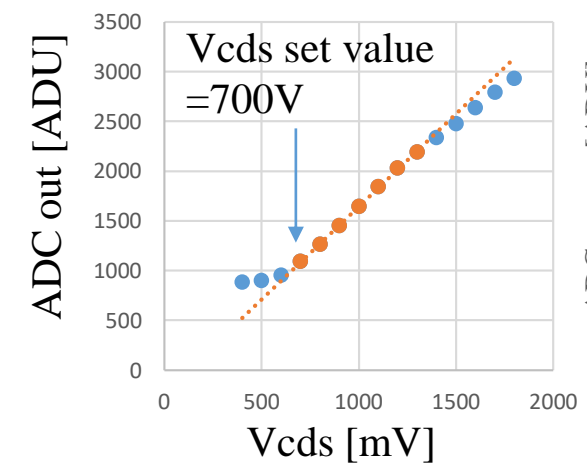
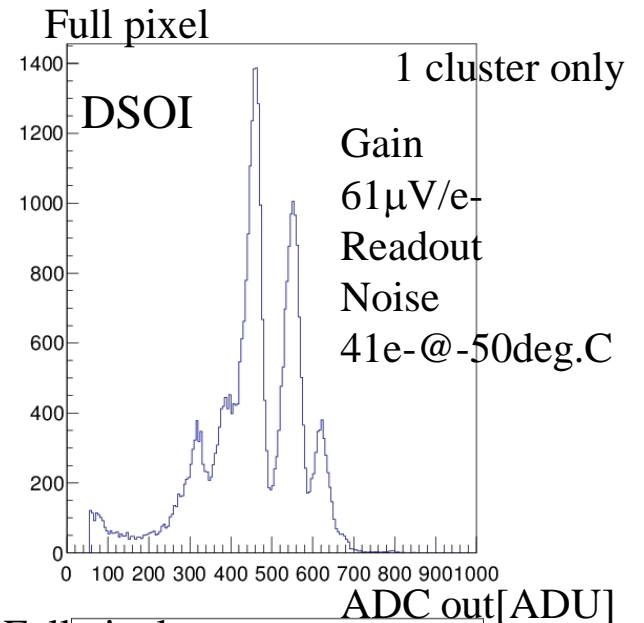
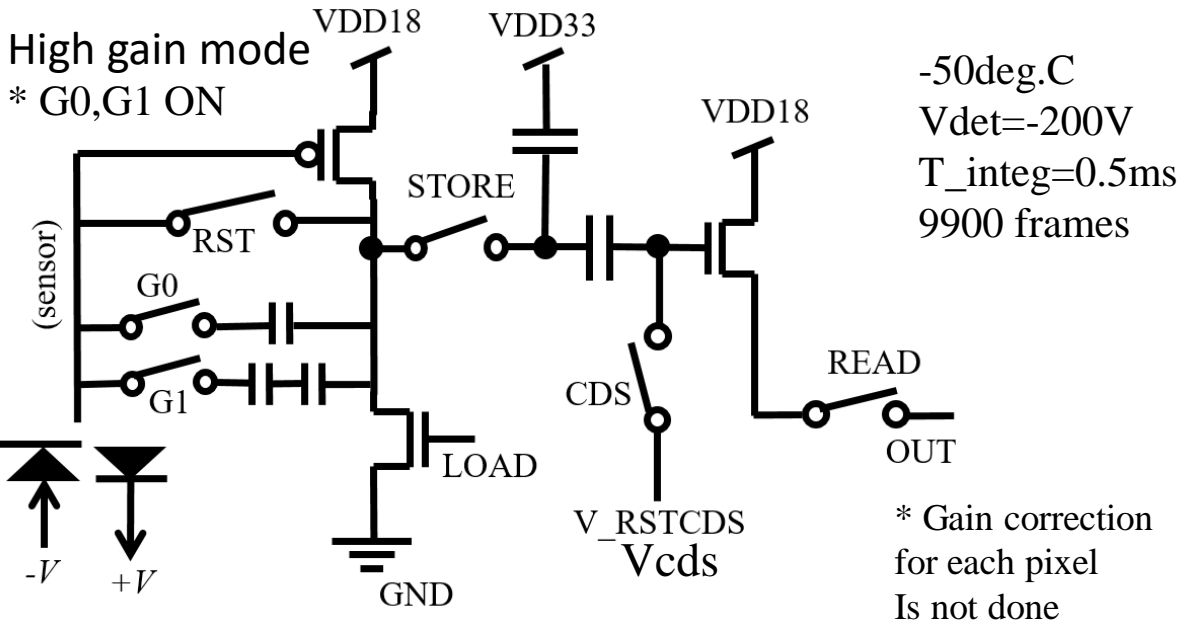


Top view



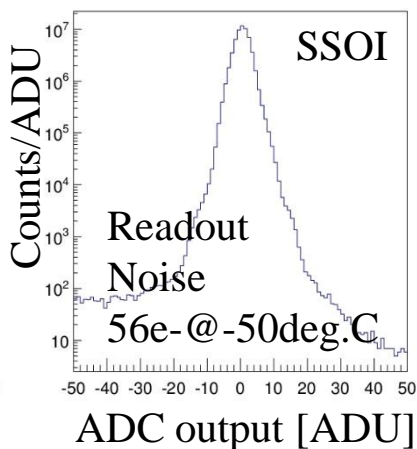
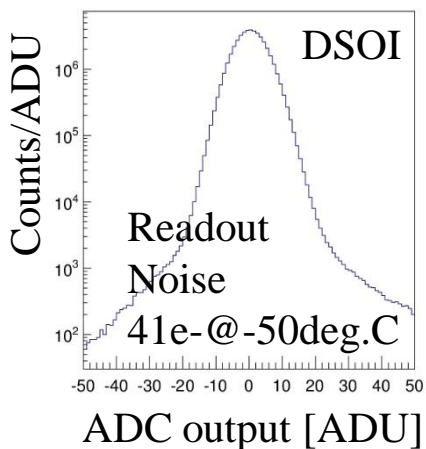
Side view

Am-241 spectra by p-type SSOI/DSOI INTPIX8



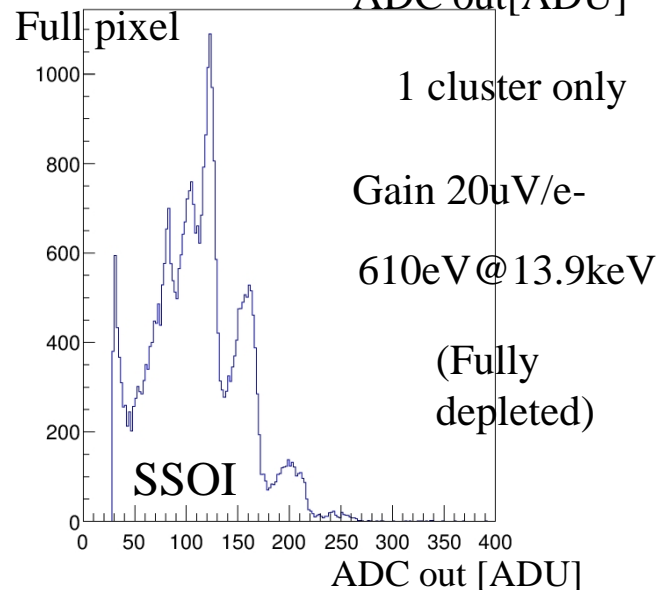
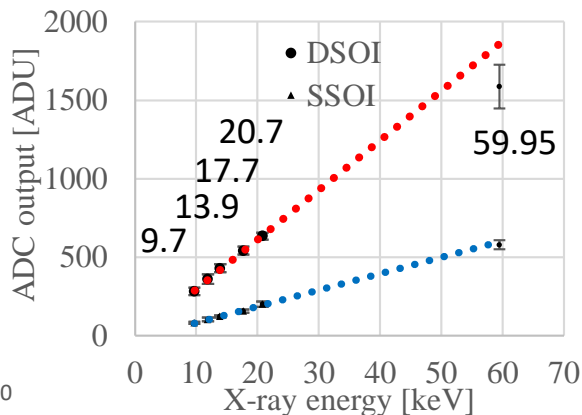
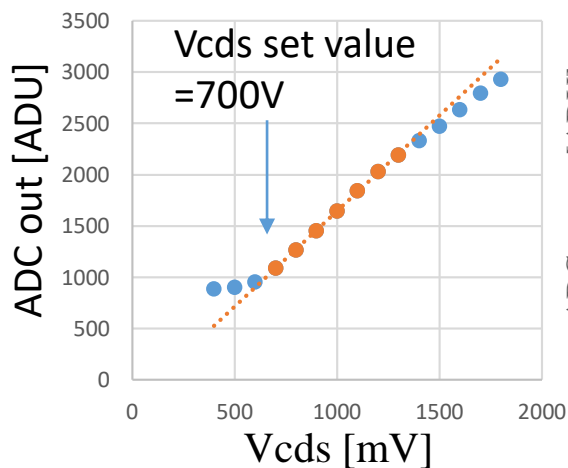
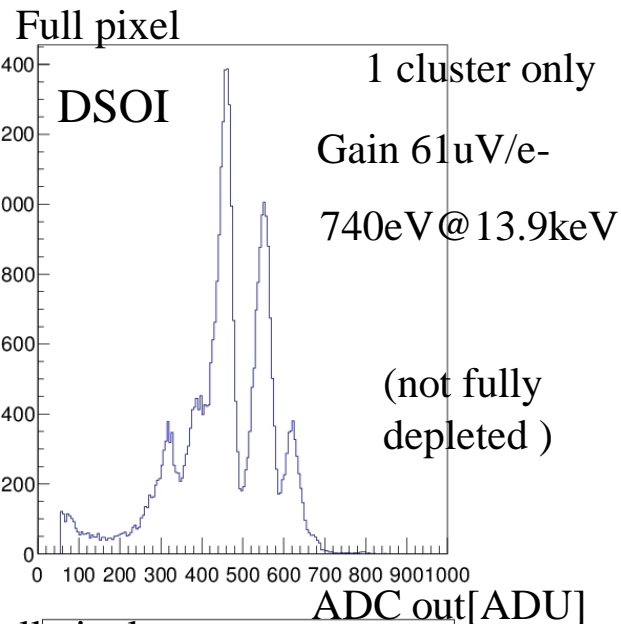
* IIN1=10mA, IIN2=7mA, IINABUF=36mA

Am-241 spectrum by p-type SSOI/DSOI INTPIX8



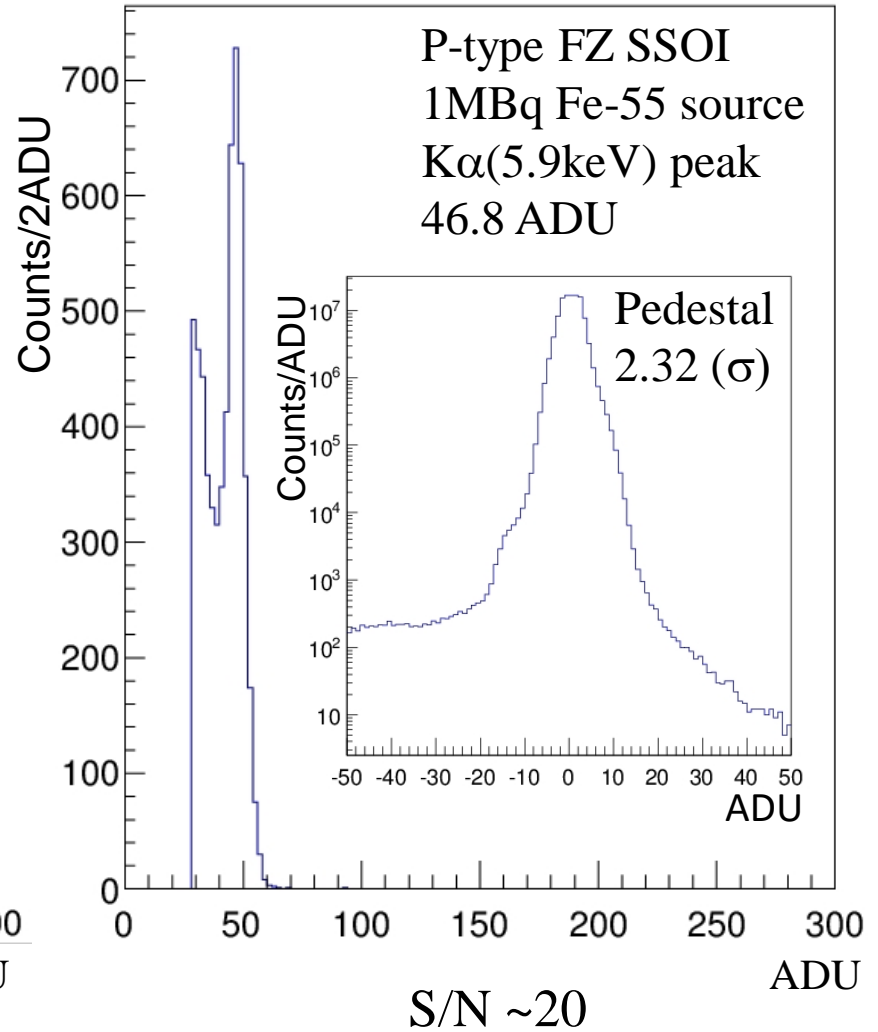
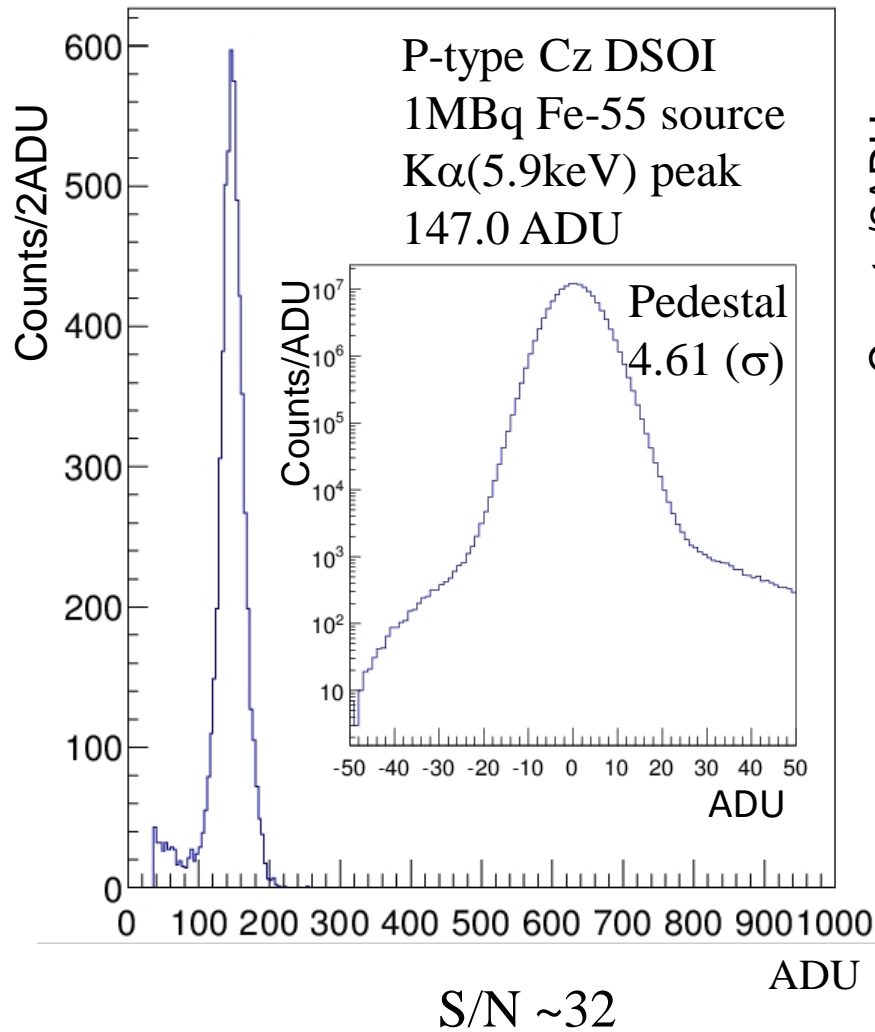
-50deg.C
Vdet=-200V
T_integ=0.5ms
9900 frames

* Gain correction
for each pixel
Is not done



* IIN1=10mA, IIN2=7mA, IINABUF=36mA

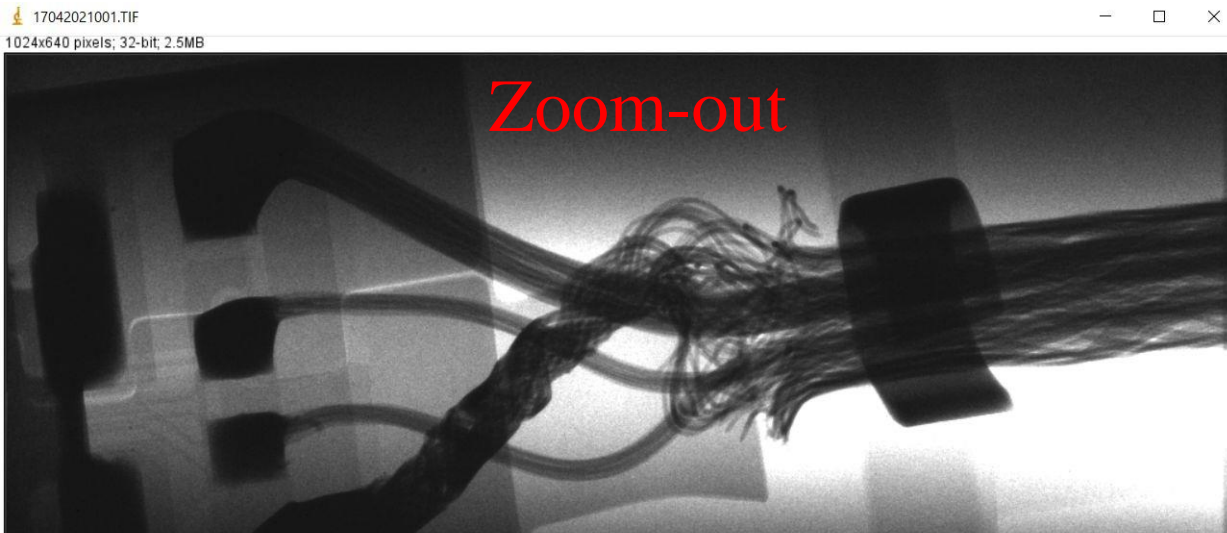
Fe-55 spectra with high gain mode



$T_{\text{integ.}}=0.5\text{ms}, V_{\text{sensor}}=-200\text{V}, -50\text{deg.C}$

Demonstration of X-ray imaging

*Preliminary
Confidential*



INTPIX8

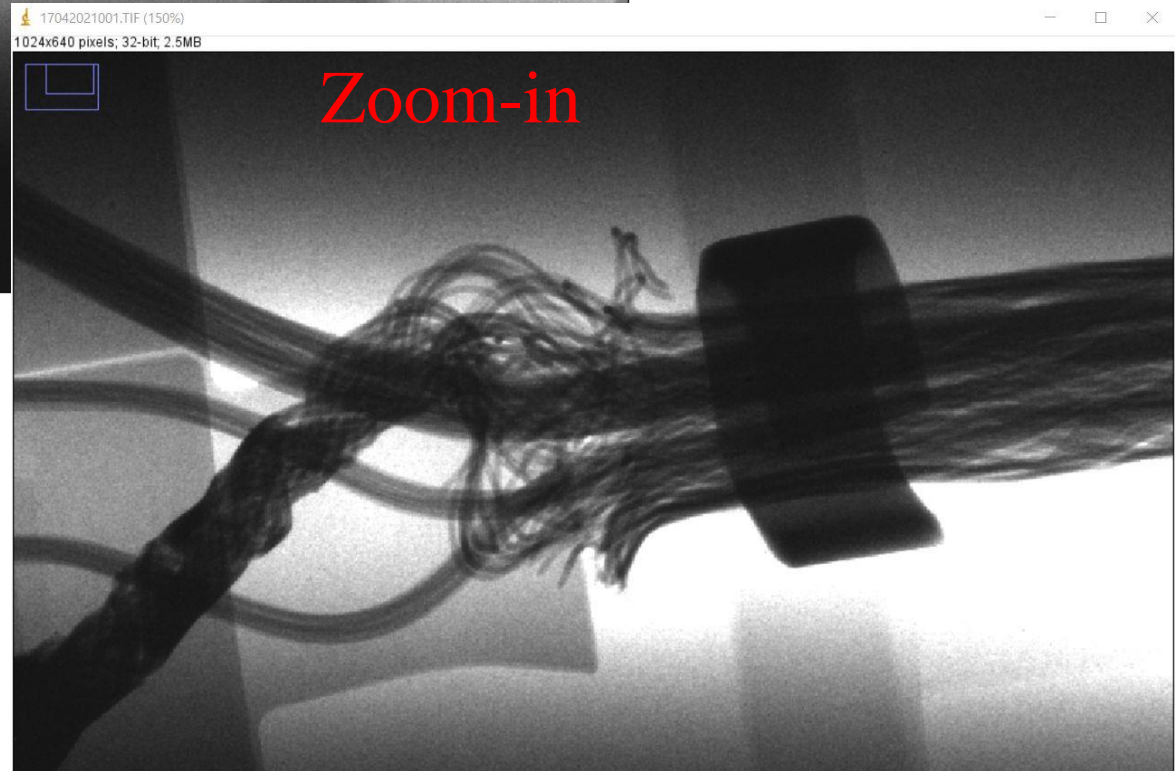
Low gain mode

40 keV Monochro. X-ray

1ms x 500 frame

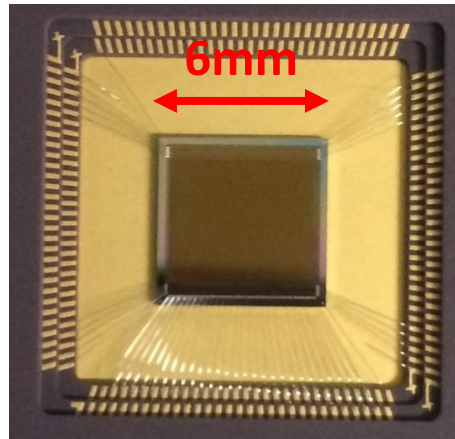
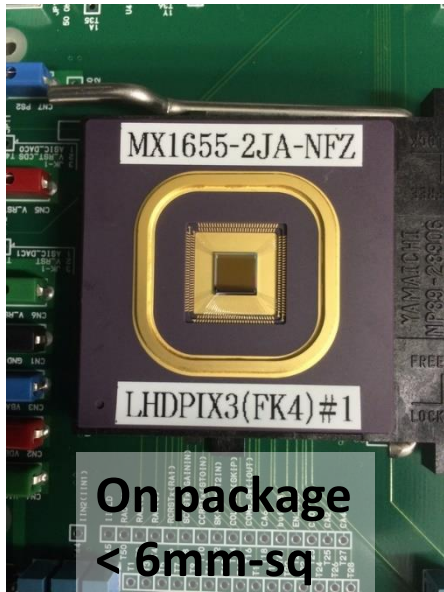
KEK PF-AR NE-7A

Beam size 40mm(H) x 4mm(V)

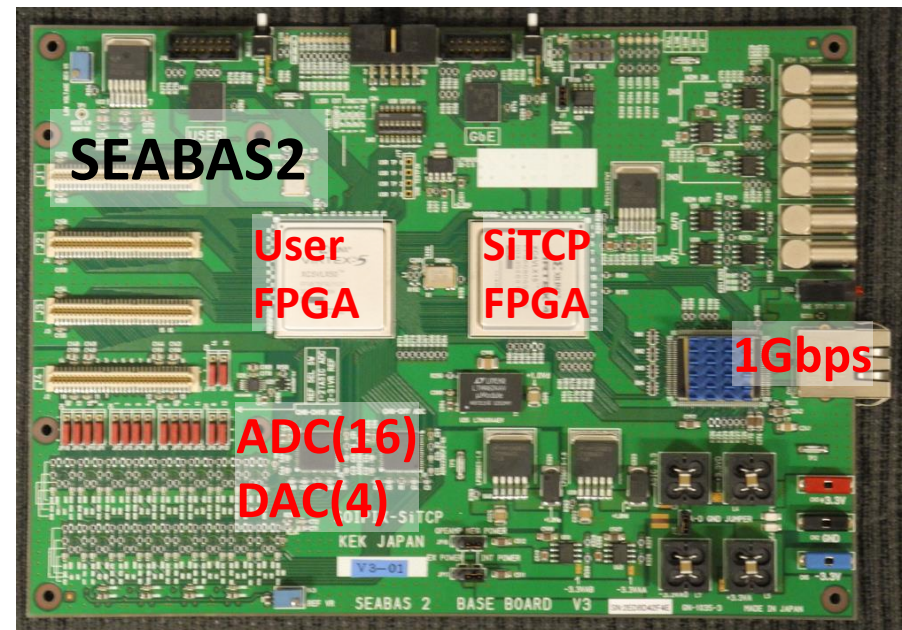
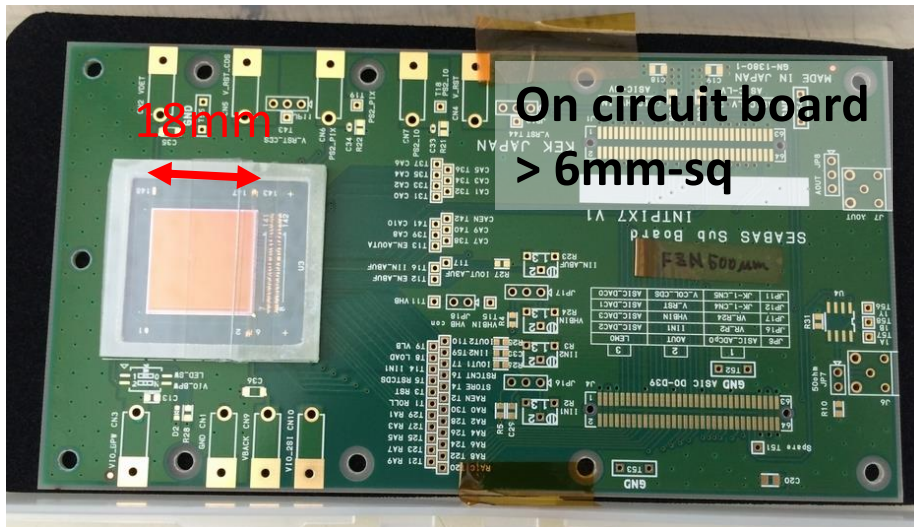
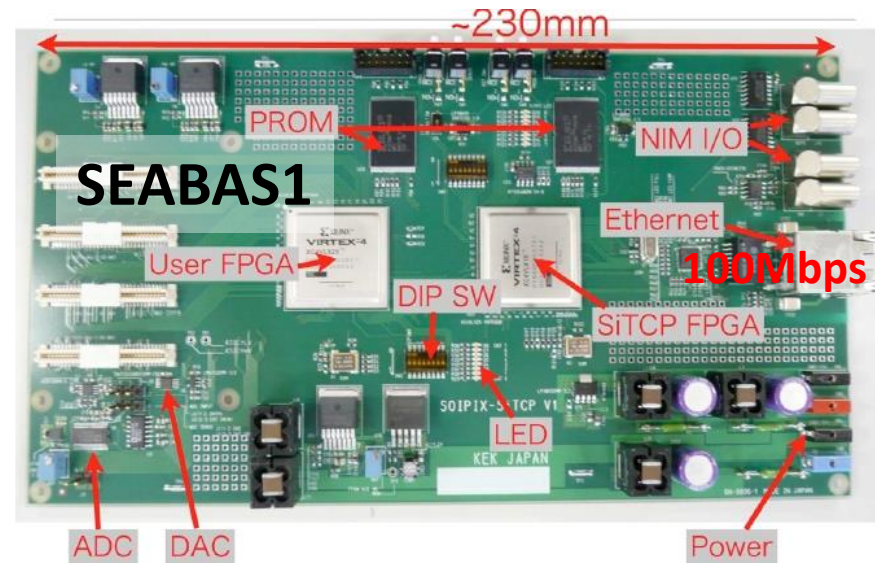


A well-known cable

Sensor test and DAQ system



A package socket is mounted on a sub circuit board



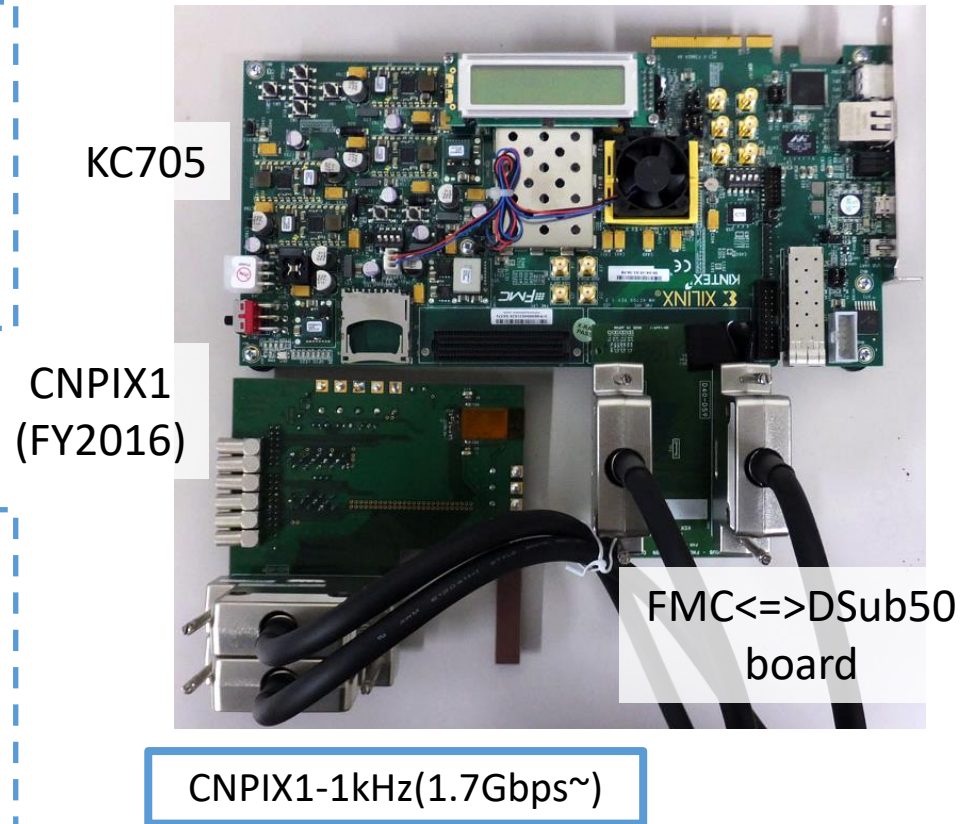
DAQ system in the future

Existing DAQ system

- SEABAS1 Vertex4
- SEABAS2 Virtex4/5
- ~7,200 slices, BlockRAM ~2,160Kb
- No DDR

Xilinx KC705 board (2017-)

- FPGA (Kintex-7)
- 50,950 slice, 16,020 Kb BlockRAM
- DDR3 memory
- Gb Ethernet, light fiber



SEABAS3 with Kintex-7 & DDR3 memory & 10 Gbps? (~2018?)

Summary & Future prospect

Integration-type pixel sensor with single/double SOI wafer
w./o. storage capacitor --- FPIX series: pixel size > 8 μm
w. storage capacitor --- INTPIX series and more: pixel size > 12 μm
New counting type pixel sensor with double SOI wafer will be developed

Future prospect

Small pixel less than 8 μm ? \rightarrow active margin, 3D chip...

Optimization/modification of storage capacitor
1.5 fF/ μm^2 \rightarrow larger capacitance per μm^2

Readout board upgrade (go to 10 Gbps?)

Integration-type pixel sensor with column ADC (DIPIX2?)

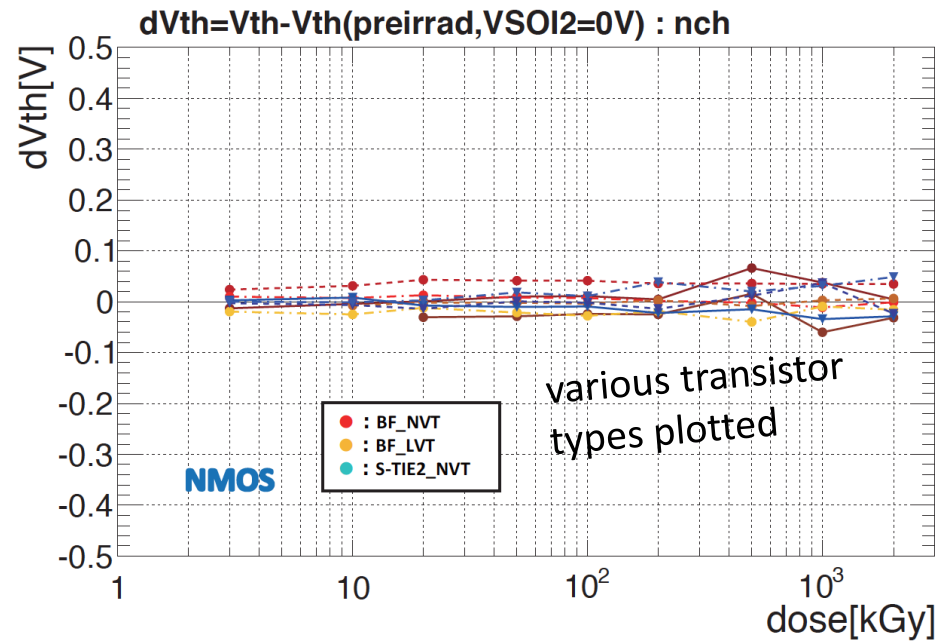
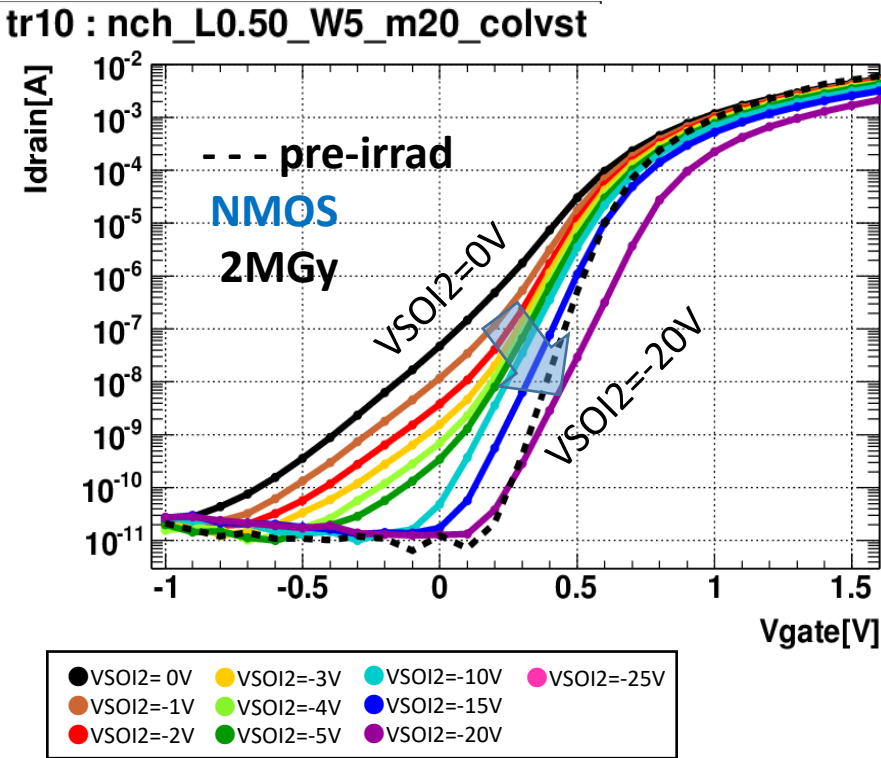
High resistivity p-type double SOI integration-type pixel sensor (INTPIX8)

supplement

FET threshold shifts and compensation in DSOI

IV curves of an NMOS (2MGy irradiated) with Changing VDSOI2

Residual of Vth shifts of various FET types (FETs grouped into 3 in VSOI2 setting)



S. Honda et al., "Total Ionization Damage Compensations in Double Silicon-on-Insulator Pixel Sensors", PoS (TIPP2014)039.

K. Hara et al., "Initial Characteristics and Radiation Damage Compensation of Double Silicon-on-Insulator Pixel Device", PoS(VERTEX2014)033.

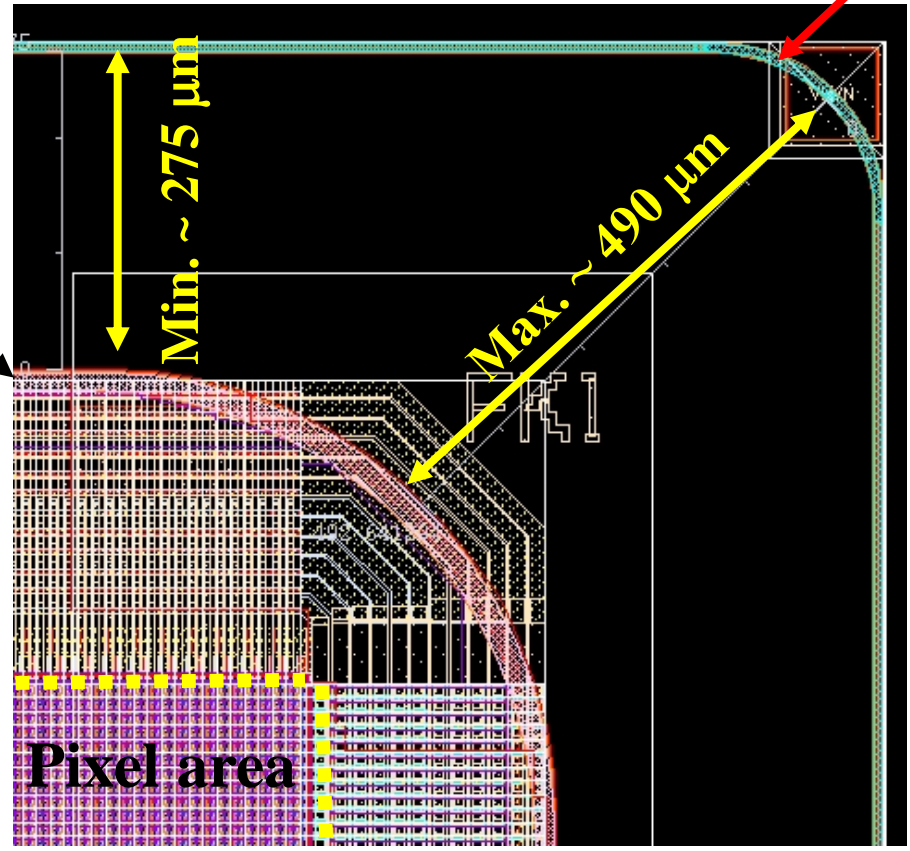
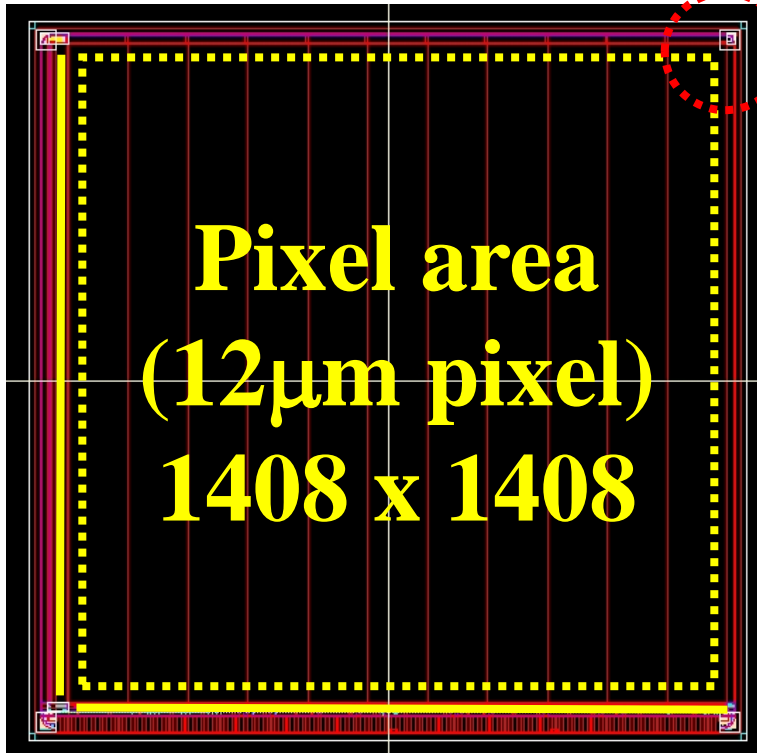
An example of Sensor layout

INTPIX7 (MPW FY13-1)

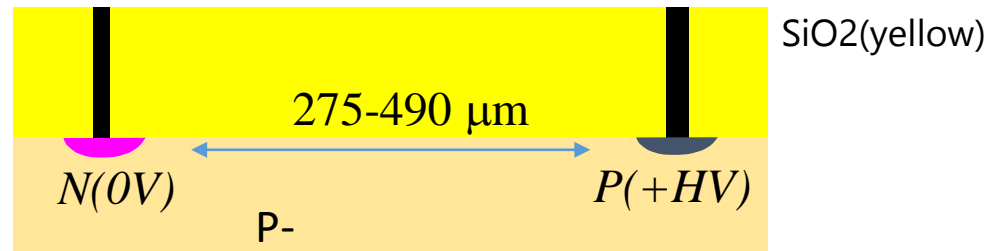
Integration-type pixel sensor

Bias ring (n+)

18mm



HV ring (p+)



Breakdown voltage ~ 600 (Max.)

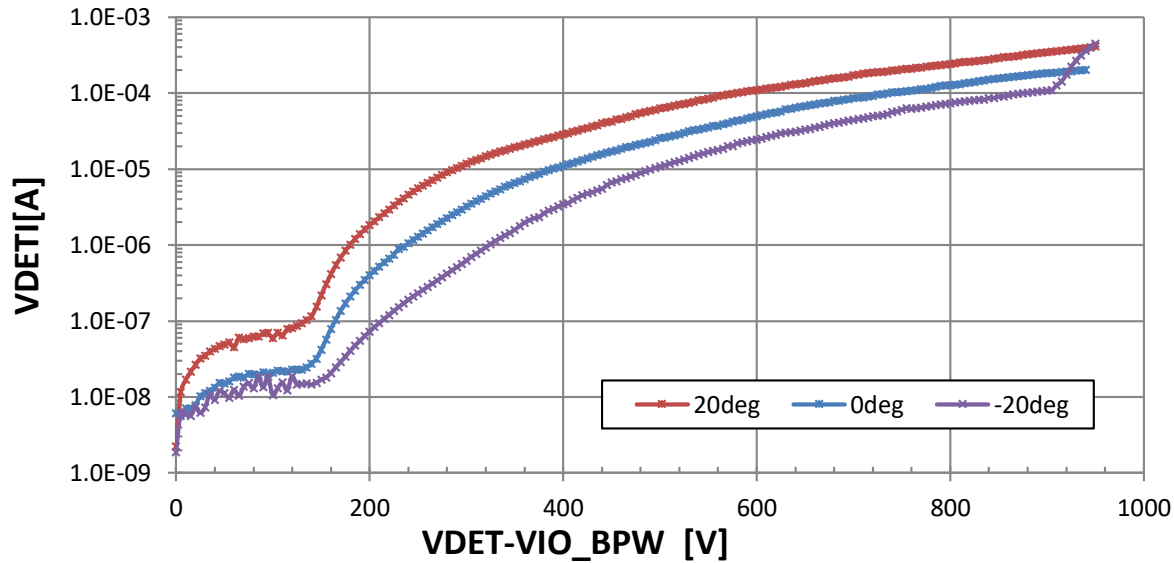
Edge of the chip (side view)

Maximum (?) breakdown voltages

MX1786-2JA-NFZ INTPIX8 Breakdown voltages

2015.9.16

VDET-VIO_BPW I-V Curve



Operation voltage is typically less than 400V

After high voltage more than 900V, the sensor got non-recoverable damage.

Therefore we don't repeat this study yet.

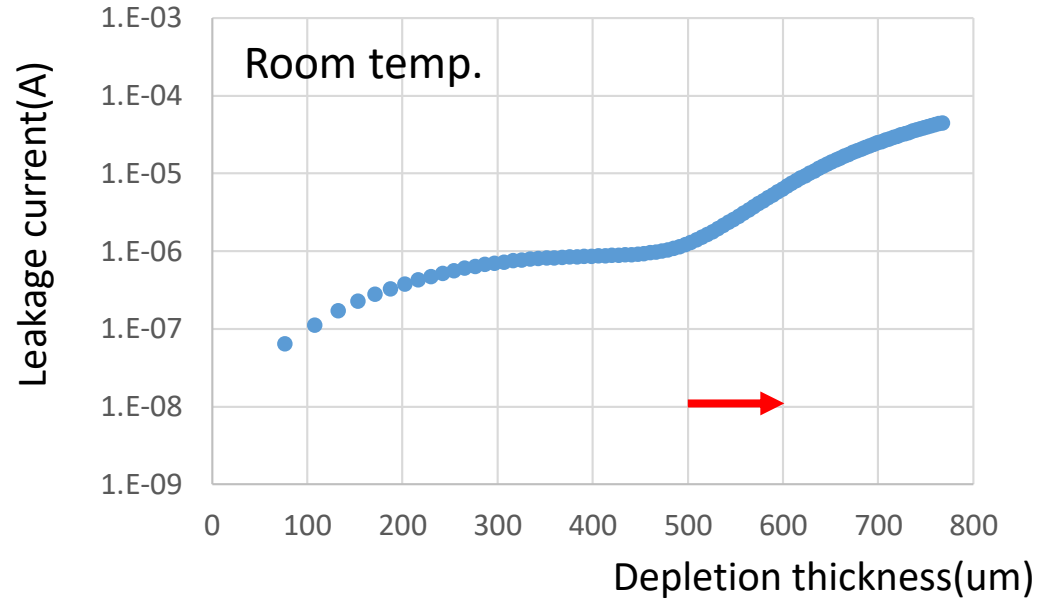
I-V curve vs depletion thickness

NFZ-INTPIX8

5 kOhm cm

Sensor thickness 500 um

Curve slope changes at over-depletion point



P-type DSOI INTPIX8

1kOhm cm

Sensor thickness 300 um

Breakdown voltage

~ -450V

Not fully depleted

